

SEARCH REQUEST FORM

Scientific and Technical Information Center

Requester's Full Name: Deno NZ Examiner #: 69332 Date: 4/21/03
 Art Unit: 171 Phone Number 308-2437 Serial Number: 101040850
 Mail Box and Bldg/Room Location: 3/4D29 Results Format Preferred (circle): PAPER DISK E-MAIL

If more than one search is submitted, please prioritize searches in order of need.

Please provide a detailed statement of the search topic, and describe as specifically as possible the subject matter to be searched. Include the elected species or structures, keywords, synonyms, acronyms, and registry numbers, and combine with the concept or utility of the invention. Define any terms that may have a special meaning. Give examples or relevant citations, authors, etc, if known. Please attach a copy of the cover sheet, pertinent claims, and abstract.

Title of Invention: _____

Inventors (please provide full names): _____

Earliest Priority Filing Date: _____

For Sequence Searches Only Please include all pertinent information (parent, child, divisional, or issued patent numbers) along with the appropriate serial number.

Formula of claim 22. Thanks.

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 Searcher Location: _____
 Date Searcher Picked Up: _____
 Date Completed: 4/22/03
 Searcher Prep & Review Time: 20
 Clerical Prep Time: _____
 Online Time: 15

Type of Search	Vendors and cost where applicable
NA Sequence (#)	STN <input checked="" type="checkbox"/>
AA Sequence (#)	Dialog _____
Structure (#)	Questel/Orbit <u>3</u>
Bibliographic	Dr. Link _____
Litigation	Lexis/Nexis _____
Fulltext	Sequence Systems _____
Patent Family	WWW/Internet _____
Other	Other (specify) _____

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DICTIONARY FILE UPDATES: 21 APR 2003 HIGHEST RN 503584-60-9

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Crossover limits have been increased. See HELP CROSSOVER for details.

Experimental and calculated property data are now available. See HELP
PROPERTIES for more information. See STNote 27, Searching Properties
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<http://www.cas.org/ONLINE/STN/STNOTES/stnotes27.pdf>

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FILE COVERS 1907 - 22 Apr 2003 VOL 138 ISS 17
FILE LAST UPDATED: 21 Apr 2003 (20030421/ED)

This file contains CAS Registry Numbers for easy and accurate
substance identification.

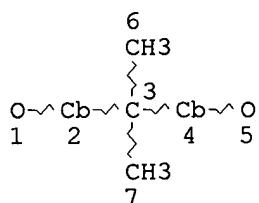
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1 2 3

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 DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:
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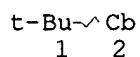
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 L4 STR 2



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STEREO ATTRIBUTES: NONE
 L5 STR 3



NODE ATTRIBUTES:
 DEFAULT MLEVEL IS ATOM
 DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:
 RING(S) ARE ISOLATED OR EMBEDDED
 NUMBER OF NODES IS 2

STEREO ATTRIBUTES: NONE

L7 SCR 2043
 L9 12 SEA FILE=REGISTRY SSS FUL L3 AND L4 AND L5 AND L7
 L10 11 SEA FILE=HCAPLUS ABB=ON L9

=> D L10 ALL 1-11 HITSTR

L10 ANSWER 1 OF 11 HCAPLUS COPYRIGHT 2003 ACS
 AN 2002:540378 HCAPLUS
 DN 137:233008
 TI The Synthesis of Poly(arylene ether)s in Solution at Pilot-Plant Scale
 with Control over Molecular Weight and End-Group Composition
 AU Bender, Timothy P.; Burt, Richard A.; Hamer, Gord K.; DeVisser, Christine;
 Smith, Paul F.; Saban, Marko
 CS Xerox Research Centre of Canada, Mississauga, ON, L5K 2L1, Can.
 SO Organic Process Research & Development (2002), 6(5), 714-720

12 polymers from
 structures 1 and 2 and 3

11 (A references

CODEN: OPRDFK; ISSN: 1083-6160

PB American Chemical Society

DT Journal

LA English

CC 35-5 (Chemistry of Synthetic High Polymers)

AB The lab.-scale optimization and pilot-plant-scale synthesis of a poly(aryl ether ketone) is reported. The polymer produced had the desired properties of low mol. wt. ($M_w = 14-15$ kD, $M_n = 6.3-6.5$ kD), reasonable polydispersity ($PD = 2.37-2.39$), and well-defined controlled end groups. This has been accomplished using a one-step soln. polymn. of 4,4'-difluorobenzophenone (DFBP), bisphenol A (BPA), and 4-tert-butylphenol (tBP). The presence or absence of a stoichiometric amt. of tBP in the polymn. reaction dictated whether the obtained polymer possessed exclusively a halide or a tert-butylphenol terminus. Simple variation of the ratio of difluorobenzophenone to BPA controls the mol. wt. of the obtained polymer without affecting the polydispersity. Several other factors were examd. to completely optimize the polymn. process: the replacement of 4,4'-difluorobenzophenone with 4,4'-dichlorobenzophenone as a cost-saving measure, the effect of temp., and the effect of the concn. of the reactants.

ST difluorobenzophenone bisphenol A butylphenol polyarylene ether prepn soln polymn; mol wt difluorobenzophenone bisphenol A butylphenol polyarylene ether

IT Polyketones

RL: EPR (Engineering process); IMF (Industrial manufacture); PEP (Physical, engineering or chemical process); PRP (Properties); PREP (Preparation); PROC (Process)
(polyether-, arom.; synthesis of poly(arylene ether)s in soln. at pilot-plant scale with control over mol. wt. and end-group compn.)

IT Polyethers, preparation

RL: EPR (Engineering process); IMF (Industrial manufacture); PEP (Physical, engineering or chemical process); PRP (Properties); PREP (Preparation); PROC (Process)
(polyketone-, arom.; synthesis of poly(arylene ether)s in soln. at pilot-plant scale with control over mol. wt. and end-group compn.)

IT Polymerization

(soln.; synthesis of poly(arylene ether)s in soln. at pilot-plant scale with control over mol. wt. and end-group compn.)

IT Molecular weight

Polydispersity

Polymerization apparatus

Safety

(synthesis of poly(arylene ether)s in soln. at pilot-plant scale with control over mol. wt. and end-group compn.)

IT 25897-65-8P, Bisphenol A-4,4'-difluorobenzophenone copolymer

27178-34-3DP, tert-Butylphenol, reaction products with bisphenol

A-difluorobenzophenone copolymer 41205-96-3P, Bisphenol

A-4,4'-dichlorobenzophenone copolymer sru 113736-28-0P, Bisphenol

A-4,4'-dichlorobenzophenone copolymer 157972-93-5DP, reaction

products with butylphenol

RL: EPR (Engineering process); IMF (Industrial manufacture); PEP (Physical, engineering or chemical process); PRP (Properties); PREP (Preparation); PROC (Process)
(synthesis of poly(arylene ether)s in soln. at pilot-plant scale with control over mol. wt. and end-group compn.)

RE.CNT 23 THERE ARE 23 CITED REFERENCES AVAILABLE FOR THIS RECORD

RE

(1) Anon; US 5739254 HCAPLUS

- (2) Anon; US 5753783 HCAPLUS
- (3) Anon; US 5761809 HCAPLUS
- (4) Anon; US 5863963 HCAPLUS
- (5) Anon; US 5907001 HCAPLUS
- (6) Anon; US 5945253 HCAPLUS
- (7) Anon; US 5958995 HCAPLUS
- (8) Anon; US 5994425 HCAPLUS
- (9) Anon; US 6020119 HCAPLUS
- (10) Anon; US 6087414 HCAPLUS
- (11) Anon; US 6090453 HCAPLUS
- (12) Anon; US 6124372 HCAPLUS
- (13) Anon; US 6139920 HCAPLUS
- (14) Anon; US 6184263 HCAPLUS
- (15) Anon; US 6187512 HCAPLUS
- (16) Cakmak, M; Plast Eng (N Y), (Handbook of Thermoplastics) 1997, V41, P931
HCAPLUS
- (17) Cotter, R; Engineering Plastics:A Handbook of Polyarylethers 1995, P28
- (18) Cotter, R; Engineering Plastics:A Handbook of Polyarylethers 1995, P289
- (19) Cotter, R; Engineering Plastics:A Handbook of Polyarylethers 1995, P45
- (20) El-Hibri, M; Plast Eng (N Y), Handbook of Thermoplastics 1997, V41, P893
HCAPLUS
- (21) Hay, A; Prog Polym Sci 1999, V24(1), P45 HCAPLUS
- (22) Labadie, J; ACS Symp Ser 1996, V624, P210 HCAPLUS
- (23) Rose, J; Polym Prepr (Am Chem Soc, Div Polym Chem) 1986, V27(1), P480
HCAPLUS

IT 157972-93-5DP, reaction products with butylphenol

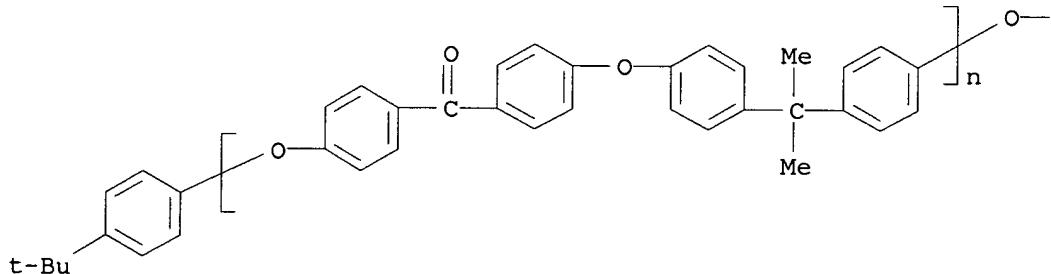
RL: EPR (Engineering process); IMF (Industrial manufacture); PEP (Physical, engineering or chemical process); PRP (Properties); PREP (Preparation); PROC (Process)

(synthesis of poly(arylene ether)s in soln. at pilot-plant scale with control over mol. wt. and end-group compn.)

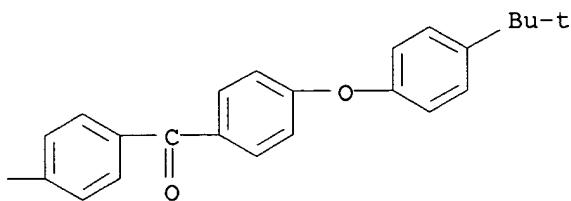
RN 157972-93-5 HCAPLUS

CN Poly[oxy-1,4-phenylene carbonyl-1,4-phenyleneoxy-1,4-phenylene(1-methylethylidene)-1,4-phenylene], .alpha.-[4-(1,1-dimethylethyl)phenyl]-.omega.-[4-[4-(1,1-dimethylethyl)phenoxy]benzoyl]phenoxy]- (9CI) (CA INDEX NAME)

PAGE 1-A



PAGE 1-B



L10 ANSWER 2 OF 11 HCAPLUS COPYRIGHT 2003 ACS
 AN 2001:832475 HCAPLUS
 DN 136:103098
 TI Thermal and mechanical properties of poly(arylene ether ketone)s based on 5-tert-butyl-1,3-bis(4-fluorobenzoyl)benzene
 AU Yildiz, Emel; Inan, Tulay Yilmaz; Yildirim, Huseyin; Kuyulu, Abdulkadir; Gungor, Attila
 CS Department of Chemical Engineering, Material and Chemical Technologies Research Institute, TUBITAK-MRC, Gebze Kocaeli, 41470, Turk.
 SO Macromolecular Materials and Engineering (2001), 286(10), 634-639
 CODEN: MMENFA; ISSN: 1438-7492
 PB Wiley-VCH Verlag GmbH
 DT Journal
 LA English
 CC 37-5 (Plastics Manufacture and Processing)
 Section cross-reference(s): 35, 36
 AB An arom. bishalide, 5-tert-butyl-1,3-bis(4-fluorobenzoyl)benzene was synthesized in high yield and purity by the reaction of 5-tert-butylisophthaloyl chloride and fluorobenzene, and polymd. by nucleophilic substitution reaction with com. available arom. bisphenols to prep. a series of high mol. wt. poly(arylene ether ketone)s contg. pendant tert-Bu groups. The effect of mol. structure on the phys., thermal, mech. and adhesion properties of the polymers was investigated.
 ST butylbisfluorobenzoylbenzene synthesis polymn bisphenol deriv polyarylene polyether polyketone; thermal mech adhesion property water absorption polymer
 IT Elongation, mechanical
 (at break; of poly(arylene ether ketone)s)
 IT Glass transition temperature
 IT Shear strength
 IT Tensile strength
 IT Viscosity
 IT Young's modulus
 (of poly(arylene ether ketone)s)
 IT Thermal stability
 (oxidative; of poly(arylene ether ketone)s)
 IT Polyketones
 RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)
 (polyether-, arom., cardo; prepn. and properties of)
 IT Polyketones
 RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)
 (polyether-, arom., fluorine-contg.; prepn. and properties of)
 IT Polyketones
 RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)
 (polyether-, arom.; prepn. and properties of)
 IT Fluoropolymers, preparation
 IT Polysulfones, preparation

IT RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation) (polyether-polyketone-, arom.; prepn. and properties of)

IT Cardo polymers

IT RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation) (polyether-polyketones, arom.; prepn. and properties of)

IT Polyketones

IT RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation) (polyether-polysulfone-, arom.; prepn. and properties of)

IT Polyethers, preparation

IT RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation) (polyketone-, arom., cardo; prepn. and properties of)

IT Polyethers, preparation

IT RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation) (polyketone-, arom., fluorine-contg.; prepn. and properties of)

IT Polyethers, preparation

IT RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation) (polyketone-, arom.; prepn. and properties of)

IT Polyethers, preparation

IT RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation) (polyketone-polysulfone-, arom.; prepn. and properties of)

IT 7732-18-5, Water, uses

IT RL: NUU (Other use, unclassified); USES (Uses) (absorption; of poly(arylene ether ketone)s)

IT 462-06-6, Fluorobenzene 2359-09-3, 5-tert-Butylisophthalic acid

IT 7719-09-7, Thionyl chloride

IT RL: RCT (Reactant); RACT (Reactant or reagent) (in prepn. of butylbisfluorobenzoylbenzene monomer)

IT 153366-73-5P 153366-74-6P **161872-40-8P** 161872-42-0P

IT 161872-44-2P 197852-95-2P 197852-98-5P 389631-66-7P

IT **389631-67-8P** 389631-68-9P 389631-69-0P 389631-70-3P

IT 389631-71-4P 389631-73-6P

IT RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation) (prepn. and properties of)

IT 153366-67-7P

IT RL: PRP (Properties); RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent) (prepn. of and in polymn. with bisphenols)

RE.CNT 9 THERE ARE 9 CITED REFERENCES AVAILABLE FOR THIS RECORD

RE

- (1) Belbin, G; Philos Trans R Soc 1987, VA322, P451
- (2) Critchely, J; Heat-resistant polymers 1983
- (3) Han, Y; Macromolecules 1995, V28, P916 HCPLUS
- (4) Hergenrother, P; Polymer 1988, V29, P358 HCPLUS
- (5) Johnson, R; US 4108837 1978 HCPLUS
- (6) Percec, V; J Polym Sci, Part A: Polym Chem 1995, V33, P331 HCPLUS
- (7) Percec, V; Macromolecules 1994, V27, P1535 HCPLUS
- (8) Selampinar, F; Synth Met 1997, V89, P111 HCPLUS
- (9) Zhang, C; Macromolecules 1993, V26, P3324 HCPLUS

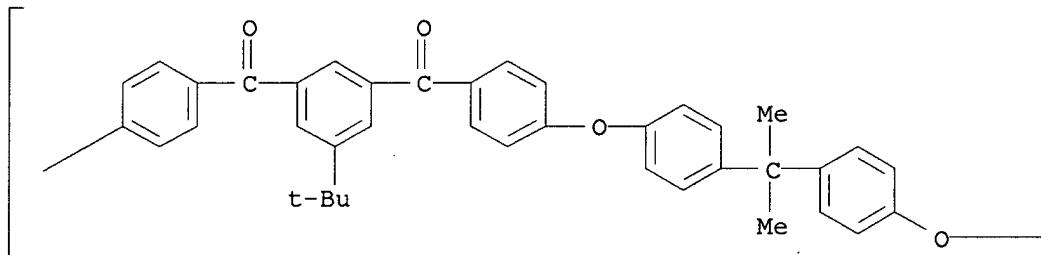
IT **161872-40-8P 389631-67-8P**

RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation) (prepn. and properties of)

RN 161872-40-8 HCPLUS

CN Poly[oxy-1,4-phenylene(1-methylethylidene)-1,4-phenyleneoxy-1,4-phenylene]carbonyl[5-(1,1-dimethylethyl)-1,3-phenylene]carbonyl-1,4-phenylene] (9CI) (CA INDEX NAME)

PAGE 1-A



PAGE 1-B

$$\left[\text{---} \right]_n$$

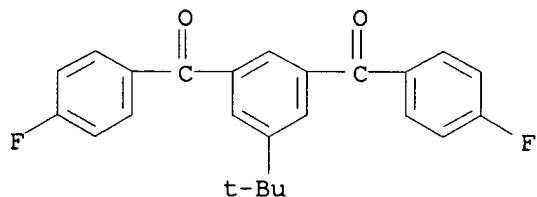
RN 389631-67-8 HCAPLUS

CN Methanone, [5-(1,1-dimethylethyl)-1,3-phenylene]bis[(4-fluorophenyl)-, polymer with 4,4'-(1-methylethylidene)bis[phenol] (9CI) (CA INDEX NAME)

CM 1

CRN 153366-67-7

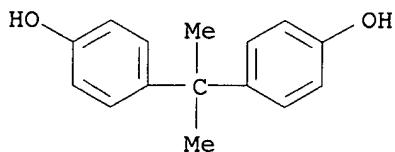
CMF C24 H20 F2 O2



CM 2

CRN 80-05-7

CMF C15 H16 O2



L10 ANSWER 3 OF 11 HCAPLUS COPYRIGHT 2003 ACS
 AN 1997:76178 HCAPLUS
 DN 126:172520
 TI Gas sorption and transport in UV-irradiated polyarylate copolymers based on tetramethylbisphenol-A and dihydroxybenzophenone
 AU Wright, C. T.; Paul, D. R.
 CS Department of Chemical Engineering and Center for Polymer Research, The University of Texas at Austin, Austin, TX, 78712, USA
 SO Journal of Membrane Science (1997), 124(2), 161-174
 CODEN: JMESDO; ISSN: 0376-7388
 PB Elsevier
 DT Journal
 LA English
 CC 38-3 (Plastics Fabrication and Uses)
 Section cross-reference(s): 36
 AB Gas sorption and transport properties at 35 .degree.C are reported for a series of UV irradiated polyarylates prep'd. from tetramethylbisphenol A (TMBPA), 4,4'-dihydroxybenzophenone (DHB), and 5-tert-Bu isophthalic acid dichloride (tBIA). UV irradn. induces crosslinking and photo-Fries rearrangements in these polymers. The gas permeability of the polyarylates decreases with UV irradn. due to redns. in the diffusion coeff.; however, the ideal selectivity for all gas pairs increases with UV irradn. The effect of UV irradn. on the gas transport properties of the polyarylates is compared with that reported in the literature for similar polyimide materials. The polyimides show much greater improvement in selectivity than do the current polyarylate materials. The photo-Fries rearrangements limit the amt. of crosslinking achievable in these polyarylate materials in spite of the fact that addnl. benzophenone units are formed.
 ST crosslinked arom polyester gas sorption permeability
 IT Polyesters, processes
 RL: PEP (Physical, engineering or chemical process); PRP (Properties);
 PROC (Process)
 (gas sorption and transport in UV-irradiated polyarylate copolymers based on tetramethylbisphenol A)
 IT Diffusion
 Solubility
 Sorption
 (gas sorption and transport in UV-irradiated polyarylate copolymers based on tetramethylbisphenol A and dihydroxybenzophenone)
 IT Permeability
 (gas; gas sorption and transport in UV-irradiated polyarylate copolymers based on tetramethylbisphenol A and dihydroxybenzophenone)
 IT Crosslinking
 Fries rearrangement
 (photochem.; gas sorption and transport in UV-irradiated polyarylate copolymers based on tetramethylbisphenol A and dihydroxybenzophenone in relation to)
 IT Polyketones

Polyketones
RL: PEP (Physical, engineering or chemical process); PRP (Properties);
PROC (Process)
(polyester-; gas sorption and transport in UV-irradiated polyarylate
copolymers based on tetramethylbisphenol A and dihydroxybenzophenone)

IT Polyketones
Polyketones
Polyketones
RL: PEP (Physical, engineering or chemical process); PRP (Properties);
PROC (Process)
(polyimide-, fluorine-contg.; gas sorption and transport in
UV-irradiated polyarylate copolymers based on tetramethylbisphenol A
and dihydroxybenzophenone and polyimides)

IT Polyketones
Polyketones
RL: PEP (Physical, engineering or chemical process); PRP (Properties);
PROC (Process)
(polyimide-; gas sorption and transport in UV-irradiated polyarylate
copolymers based on tetramethylbisphenol A and dihydroxybenzophenone
and polyimides)

IT Fluoropolymers, processes
RL: PEP (Physical, engineering or chemical process); PRP (Properties);
PROC (Process)
(polyimide-polyketone-; gas sorption and transport in UV-irradiated
polyarylate copolymers based on tetramethylbisphenol A and
dihydroxybenzophenone and polyimides)

IT Polyimides, processes
Polyimides, processes
Polyimides, processes
RL: PEP (Physical, engineering or chemical process); PRP (Properties);
PROC (Process)
(polyketone-, fluorine-contg.; gas sorption and transport in
UV-irradiated polyarylate copolymers based on tetramethylbisphenol A
and dihydroxybenzophenone and polyimides)

IT Polyesters, processes
Polyesters, processes
RL: PEP (Physical, engineering or chemical process); PRP (Properties);
PROC (Process)
(polyketone-; gas sorption and transport in UV-irradiated polyarylate
copolymers based on tetramethylbisphenol A and dihydroxybenzophenone)

IT Polyimides, processes
Polyimides, processes
RL: PEP (Physical, engineering or chemical process); PRP (Properties);
PROC (Process)
(polyketone-; gas sorption and transport in UV-irradiated polyarylate
copolymers based on tetramethylbisphenol A and dihydroxybenzophenone
and polyimides)

IT 139198-06-4, 5-tert-Butylisophthaloyl chloride-tetramethylbisphenol A
copolymer 139198-29-1, 5-tert-Butylisophthaloyl chloride-
tetramethylbisphenol A copolymer, SRU
RL: PEP (Physical, engineering or chemical process); PRP (Properties);
PROC (Process)
(gas sorption and transport in UV-irradiated polyarylate copolymers
based on tetramethylbisphenol A)

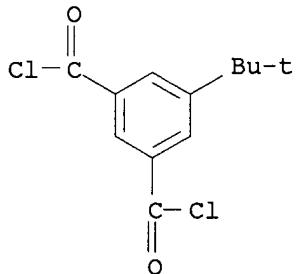
IT 74-82-8, Methane, uses 124-38-9, Carbon dioxide, uses 1333-74-0,
Hydrogen, uses 7727-37-9, Nitrogen, uses 7782-44-7, Oxygen, uses
RL: NUU (Other use, unclassified); USES (Uses)
(gas sorption and transport in UV-irradiated polyarylate copolymers

IT based on tetramethylbisphenol A and dihydroxybenzophenone)
187083-63-2, 5-tert-Butylisophthaloyl chloride-4,4'-
dihydroxybenzophenone-tetramethylbisphenol A copolymer
RL: PEP (Physical, engineering or chemical process); PRP (Properties);
PROC (Process)
(gas sorption and transport in UV-irradiated polyarylate copolymers
based on tetramethylbisphenol A and dihydroxybenzophenone)
96126-64-6, 3,3',4,4'-Benzophenonetetracarboxylic dianhydride-2,4,6-
trimethyl-1,3-phenylenediamine copolymer, SRU 96211-26-6,
3,3',4,4'-Benzophenonetetracarboxylic dianhydride-2,4,6-trimethyl-1,3-
phenylenediamine copolymer 115864-42-1, 3,3',4,4'-
Benzophenonetetracarboxylic dianhydride-2,2-bis(3,4-
dicarboxyphenyl)hexafluoropropane dianhydride-2,4,6-trimethyl-1,3-
phenylenediamine copolymer
RL: PEP (Physical, engineering or chemical process); PRP (Properties);
PROC (Process)
(gas sorption and transport in UV-irradiated polyarylate copolymers
based on tetramethylbisphenol A and dihydroxybenzophenone and
polyimides)
IT **187083-63-2**, 5-tert-Butylisophthaloyl chloride-4,4'-
dihydroxybenzophenone-tetramethylbisphenol A copolymer
RL: PEP (Physical, engineering or chemical process); PRP (Properties);
PROC (Process)
(gas sorption and transport in UV-irradiated polyarylate copolymers
based on tetramethylbisphenol A and dihydroxybenzophenone)
RN 187083-63-2 HCAPLUS
CN 1,3-Benzenedicarbonyl dichloride, 5-(1,1-dimethylethyl)-, polymer with
bis(4-hydroxyphenyl)methanone and 4,4'-(1-methylethylidene)bis[2,6-
dimethylphenol] (9CI) (CA INDEX NAME)

CM 1

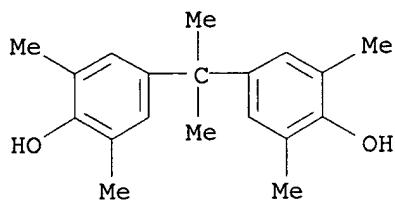
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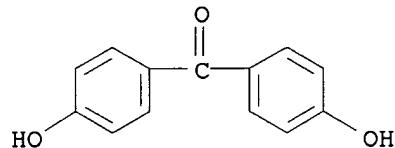


CM 2

CRN 5613-46-7
CMF C19 H24 02



CM 3

CRN 611-99-4
CMF C13 H10 O3

L10 ANSWER 4 OF 11 HCAPLUS COPYRIGHT 2003 ACS
 AN 1995:388056 HCAPLUS
 DN 122:188320
 TI Synthesis of high molecular weight poly(ether ketone)s by polycondensation of activated bis(aryl chloride)s with bisphenolates
 AU Percec, V.; Grigoras, M.; Clough, R. S.; Fanjul, J.
 CS Dep. of Macromolecular Science, Case Western Reserve Univ., Cleveland, OH, 44106, USA
 SO Journal of Polymer Science, Part A: Polymer Chemistry (1995), 33(2), 331-44
 CODEN: JPACEC; ISSN: 0887-624X
 PB Wiley
 DT Journal
 LA English
 CC 35-5 (Chemistry of Synthetic High Polymers)
 AB Polyether-polyketones were prepd. by polycondensation of bis(aryl chlorides) with bisphenols; e.g., 1,3-bis(4-chlorobenzoyl)-5-tert-butylbenzene or 2,2'-bis(4-chlorobenzoyl)biphenyl with various bisphenols, and 2,2'-bis(4-hydroxyphenoxy)biphenyl with 4,4'-dichlorobenzophenone or 1,3-bis(4-chlorobenzoyl)benzene. The specific reaction conditions required to obtain high mol. wt. polymers are reported.
 ST high mol wt polyether polyketone
 IT Polyketones
 RL: SPN (Synthetic preparation); PREP (Preparation)
 (polyether-, arom., prepn. of high mol. wt.)
 IT Polyketones
 RL: SPN (Synthetic preparation); PREP (Preparation)
 (polyether-polythioether-, arom., prepn. of high mol. wt.)
 IT Polyethers, preparation
 RL: SPN (Synthetic preparation); PREP (Preparation)
 (polyketone-, arom., prepn. of high mol. wt.)
 IT Polyethers, preparation
 RL: SPN (Synthetic preparation); PREP (Preparation)

(polyketone-polythioether-, arom., prepn. of high mol. wt.)

IT Polyethers, preparation
 RL: SPN (Synthetic preparation); PREP (Preparation)
 (thio-, polyether-polyketone-, arom., prepn. of high mol. wt.)

IT 2479-46-1P 13118-94-0P, 1,3-Bis(4-Nitrophenoxy)benzene 65801-73-2P,
 4,4'-(2,2'-Biphenylylenedioxy)dianiline 65811-03-2P,
 2,2'-(4-Nitrophenoxy)biphenyl
 RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT
 (Reactant or reagent)
 (intermediate; in prepn. of high mol. wt. polyether-polyketones)

IT 126716-90-3P, 4,4'-(m-Phenylenedioxy)diphenol 135208-37-6P,
 4,4'-(2,2'-Biphenylylenedioxy)diphenol 153366-66-6P,
 1-tert-Butyl-3,5-bis(4-chlorobenzoyl)benzene 153366-67-7P,
 1-tert-Butyl-3,5-bis(4-fluorobenzoyl)benzene
 RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT
 (Reactant or reagent)
 (monomer; in prepn. of high mol. wt. polyether-polyketones)

IT 118455-24-6P, 2,2'-Biphenyldiol-4,4'-difluorobenzophenone copolymer sru
 118455-25-7P, 2,2'-Biphenyldiol-1,4-bis(4-fluorobenzoyl)benzene copolymer
 sru 135142-80-2P, 4,4'-(2,2'-Biphenylylenedioxy)diphenol-4,4'-
 difluorobenzophenone copolymer sru 135208-38-7P, 4,4'-(2,2'-
 Biphenylylenedioxy)diphenol-4,4'-difluorobenzophenone copolymer
 143566-14-7P, 2,2'-Bis(4-fluorobenzoyl)biphenyl-hydroquinone copolymer
 143566-16-9P, 2,2'-Bis(4-fluorobenzoyl)biphenyl-bisphenol A copolymer
 143566-17-0P, 2,2'-Bis(4-fluorobenzoyl)biphenyl-bisphenol A copolymer sru
 143566-19-2P, 2,2'-Bis(4-fluorobenzoyl)biphenyl-hydroquinone copolymer sru
 153366-71-3P, 1-tert-Butyl-3,5-bis(p-chlorobenzoyl)benzene-4,4'-
 oxydiphenol copolymer sru 153366-72-4P, 1-tert-Butyl-3,5-bis(p-
 chlorobenzoyl)benzene-4,4'-oxydiphenol copolymer 153366-73-5P,
 1-tert-Butyl-3,5-bis(p-fluorobenzoyl)benzene-hydroquinone copolymer
 153366-74-6P, 1-tert-Butyl-3,5-bis(p-fluorobenzoyl)benzene-hydroquinone
 copolymer sru 153366-75-7P, 1-tert-Butyl-3,5-bis(p-chlorobenzoyl)benzene-
 hydroquinone copolymer **161872-39-5P**, Bisphenol
 A-1-tert-butyl-3,5-bis(p-chlorobenzoyl)benzene copolymer
161872-40-8P, Bisphenol A-1-tert-butyl-3,5-bis(p-
 chlorobenzoyl)benzene copolymer sru 161872-41-9P, 1-tert-Butyl-3,5-bis(p-
 chlorobenzoyl)benzene-4,4'-thiodiphenol copolymer 161872-42-0P,
 1-tert-Butyl-3,5-bis(p-chlorobenzoyl)benzene-4,4'-thiodiphenol copolymer
 sru 161872-43-1P, 4,4'-Biphenyldiol-1-tert-butyl-3,5-bis(p-
 chlorobenzoyl)benzene copolymer 161872-44-2P, 4,4'-Biphenyldiol-1-tert-
 butyl-3,5-bis(p-chlorobenzoyl)benzene copolymer sru 161872-45-3P,
 4,4'-(2,2'-Biphenylylenedioxy)diphenol-4,4'-dichlorobenzophenone copolymer
 161872-46-4P, 4,4'-(2,2'-Biphenylylenedioxy)diphenol-1,3-bis(4-
 fluorobenzoyl)benzene copolymer 161872-47-5P, 4,4'-(2,2'-
 Biphenylylenedioxy)diphenol-1,3-bis(4-fluorobenzoyl)benzene copolymer sru
 161872-48-6P, 4,4'-(2,2'-Biphenylylenedioxy)diphenol-1,3-bis(4-
 chlorobenzoyl)benzene copolymer 161872-49-7P, 2,2'-Bis(4-
 chlorobenzoyl)biphenyl-hydroquinone copolymer 161872-50-0P,
 2,2'-Bis(4-chlorobenzoyl)biphenyl-bisphenol A copolymer 161872-51-1P,
 2,2'-Bis(4-fluorobenzoyl)biphenyl-4,4'-oxydiphenol copolymer
 161872-52-2P, 2,2'-Bis(4-fluorobenzoyl)biphenyl-4,4'-oxydiphenol copolymer
 sru 161872-53-3P, 2,2'-Bis(4-chlorobenzoyl)biphenyl-4,4'-oxydiphenol
 copolymer 161872-54-4P, 2,2'-Bis(4-fluorobenzoyl)biphenyl-4,4'-
 (p-phenylenedioxy)diphenol copolymer 161872-55-5P, 2,2'-Bis(4-
 fluorobenzoyl)biphenyl-4,4'-(p-phenylenedioxy)diphenol copolymer sru
 161872-56-6P, 2,2'-Bis(4-chlorobenzoyl)biphenyl-4,4'-(p-
 phenylenedioxy)diphenol copolymer 161872-57-7P, 2,2'-Bis(4-
 fluorobenzoyl)biphenyl-4,4'-(m-phenylenedioxy)diphenol copolymer

161872-58-8P, 2,2'-Bis(4-fluorobenzoyl)biphenyl-4,4'-(m-phenylenedioxy)diphenol copolymer sru 161872-59-9P, 2,2'-Bis(4-chlorobenzoyl)biphenyl-4,4'-(m-phenylenedioxy)diphenol copolymer 161872-60-2P, 4,4'-(2,2'-Biphenylylenedioxy)diphenol-2,2'-bis(4-fluorobenzoyl)biphenyl copolymer 161872-61-3P, 4,4'-(2,2'-Biphenylylenedioxy)diphenol-2,2'-bis(4-fluorobenzoyl)biphenyl copolymer sru 161872-62-4P, 4,4'-(2,2'-Biphenylylenedioxy)diphenol-2,2'-bis(4-chlorobenzoyl)biphenyl copolymer 161872-63-5P, Catechol-2,2'-bis(4-fluorobenzoyl)biphenyl copolymer 161872-64-6P, Catechol-2,2'-bis(4-fluorobenzoyl)biphenyl copolymer sru 161872-65-7P, 3,3'-Biphenyldiol-2,2'-bis(4-fluorobenzoyl)biphenyl copolymer 161872-66-8P, 3,3'-Biphenyldiol-2,2'-bis(4-fluorobenzoyl)biphenyl copolymer sru 161872-67-9P, 2,2'-Biphenyldiol-4,4'-difluorobenzophenone copolymer 161872-68-0P, 2,2'-Biphenyldiol-1,3-bis(4-fluorobenzoyl)benzene copolymer 161872-69-1P, 2,2'-Biphenyldiol-1,3-bis(4-fluorobenzoyl)benzene copolymer sru 161872-70-4P, 2,2'-Biphenyldiol-1,4-bis(4-fluorobenzoyl)benzene copolymer 161872-71-5P, 2,2'-Biphenyldiol-4,4'-dichlorobenzophenone copolymer 161872-72-6P, 2,2'-Biphenyldiol-1,3-bis(p-chlorobenzoyl)benzene copolymer

RL: SPN (Synthetic preparation); PREP (Preparation)
(prepn. of high mol. wt. polyether-polyketones)

IT 2359-09-3, 5-tert-Butylisophthalic acid
RL: RCT (Reactant); RACT (Reactant or reagent)
(reactant; in prepn. of high mol. wt. polyether-polyketones)

IT 100-00-5, p-Chloronitrobenzene 108-46-3, 1,3-Benzenediol, reactions
108-90-7, Chlorobenzene, reactions 462-06-6, Fluorobenzene 1806-29-7,
2,2'-Biphenyldiol
RL: RCT (Reactant); RACT (Reactant or reagent)
(starting material; in prepn. of high mol. wt. polyether-polyketones)

IT 161872-39-5P, Bisphenol A-1-tert-butyl-3,5-bis(p-chlorobenzoyl)benzene copolymer 161872-40-8P, Bisphenol A-1-tert-butyl-3,5-bis(p-chlorobenzoyl)benzene copolymer sru
RL: SPN (Synthetic preparation); PREP (Preparation)
(prepn. of high mol. wt. polyether-polyketones)

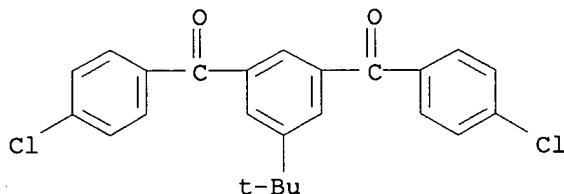
RN 161872-39-5 HCPLUS

CN Methanone, [5-(1,1-dimethylethyl)-1,3-phenylene]bis[(4-chlorophenyl)-, polymer with 4,4'-(1-methylethylidene)bis[phenol] (9CI) (CA INDEX NAME)

CM 1

CRN 153366-66-6

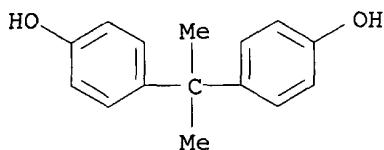
CMF C24 H20 Cl12 O2



CM 2

CRN 80-05-7

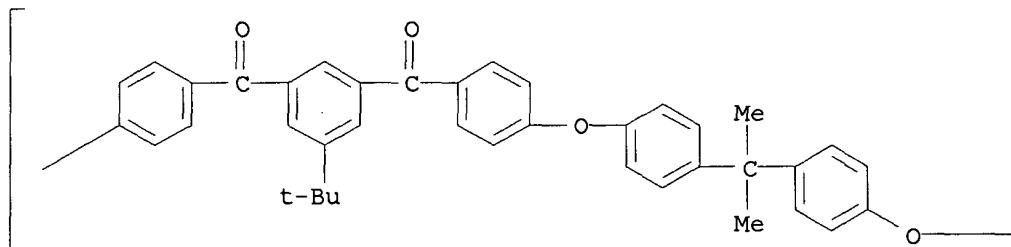
CMF C15 H16 O2



RN 161872-40-8 HCAPLUS

CN Poly[oxy-1,4-phenylene(1-methylethylidene)-1,4-phenyleneoxy-1,4-phenylene]carbonyl[5-(1,1-dimethylethyl)-1,3-phenylene]carbonyl-1,4-phenylene] (9CI) (CA INDEX NAME)

PAGE 1-A



PAGE 1-B



L10 ANSWER 5 OF 11 HCAPLUS COPYRIGHT 2003 ACS

AN 1994:580888 HCAPLUS

DN 121:180888

TI Amorphous bisphenol-A based poly(arylene ether) modified cyanate ester networks

AU Srinivasan, S. A.; McGrath, J. E.

CS Dep. Chem., Virginia Polytech. Inst. and State Univ., Blacksburg, VA, 24061-0212, USA

SO High Performance Polymers (1993), 5(4), 259-74
CODEN: HPPOEX; ISSN: 0954-0083

DT Journal

LA English

CC 37-5 (Plastics Manufacture and Processing)

AB Cyanate ester or triazine networks are receiving considerable attention as potential candidates for high-temp. adhesives and composite matrixes. Low

toughness is a major drawback with most crosslinked thermosetting materials, including the cyanate ester networks. Considerable attention has been devoted to the aspect of toughening such brittle networks in the authors' labs. Reactive functional thermoplastic toughness modifiers not only enhance toughness but also permit highly desirable stability to solvent stress cracking without seriously affecting the moderately high modulus. The authors have earlier reported on various aspects of this technol. as applied to epoxy and bismaleimide systems. Careful control of the heterophase morphol. structure is necessary to achieve significant toughening. In the present work, the authors have focused on modifications of a specific cyanate ester network system based on bisphenol-A with thermoplastic modifiers of varying backbone mol. wt. and chem. In particular, hydroxyl or cyanato functional bisphenol A-based amorphous poly(arylene ether sulfone)s and poly(arylene ether ketone)s have been successfully utilized. Blends of reactive and non-reactive polysulfones were also useful tougheners, apparently by allowing phase-size control. The use of poly(aryl ether ketone)s (which are of lower polarity than the polyarylene ether sulfones) resulted in larger, well-defined morphols., which in turn afforded tougher networks. Either hydroxyl or cyanato reactive end groups could be effectively utilized. Both were superior to non-reactive systems in terms of both mech. performance and solvent stability.

ST polyisocyanurate toughened polyether polysulfone; polyketone polyether toughener polyisocyanurate

IT Polyisocyanurates

RL: PRP (Properties)
(mech. and morphol. properties of polyether-polyketone- or polyether-polysulfone-toughened)

IT Impact-resistant materials
(mech. and morphol. properties of polyisocyanurate toughened with polyether-polyketones or polyether-polysulfones)

IT Glass temperature and transition
(of polyether-polyketone or polyether-polysulfone tougheners for polyisocyanurates)

IT Polymer morphology
(of polyisocyanurate toughened with polyether-polyketones or polyether-polysulfones)

IT Polyketones

Polysulfones, properties

RL: PRP (Properties)
(polyether-, mech. and morphol. properties of polyisocyanurate toughened with)

IT Polyethers, properties

RL: PRP (Properties)
(polyketone-, mech. and morphol. properties of polyisocyanurate toughened with)

IT Polyethers, properties

RL: PRP (Properties)
(polysulfone-, mech. and morphol. properties of polyisocyanurate toughened with)

IT 1156-51-0, Arocy B10

RL: PRP (Properties)
(mech. and morphol. properties of polyether-polyketone- or polyether-polysulfone-toughened)

IT 98-54-4D, 4-t-Butylphenol, reaction products with polyether-polyketones or polyether-polysulfones 506-68-3D, Bromocyanide, reaction products with polyether-polyketones or polyether-polysulfones 25135-51-7 25154-01-2, Bisphenol A-4,4'-dichlorodiphenylsulfone copolymer 25154-01-2D,

Bisphenol A-4,4'-dichlorodiphenylsulfone copolymer, reaction products with bromocyanide 41205-96-3 113736-28-0, Bisphenol A-4,4'-dichlorobenzophenone copolymer 113736-28-0D, reaction products with bromocyanide 118543-03-6 157972-92-4 **157972-93-5**

RL: PRP (Properties)

(mech. and morphol. properties of polyisocyanurate toughened with)

IT **157972-93-5**

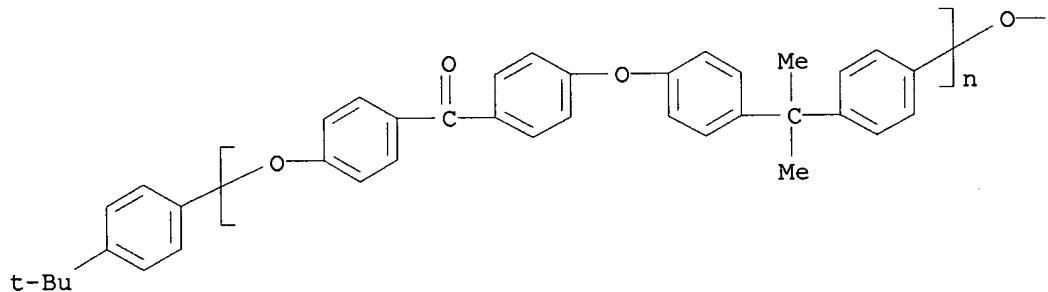
RL: PRP (Properties)

(mech. and morphol. properties of polyisocyanurate toughened with)

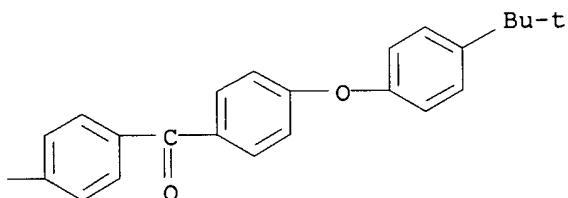
RN 157972-93-5 HCPLUS

CN Poly[oxy-1,4-phenylene carbonyl-1,4-phenyleneoxy-1,4-phenylene(1-methylethylidene)-1,4-phenylene], .alpha.-[4-(1,1-dimethylethyl)phenyl]-.omega.-[4-[4-(1,1-dimethylethyl)phenoxy]benzoyl]phenoxy]- (9CI) (CA INDEX NAME)

PAGE 1-A



PAGE 1-B



L10 ANSWER 6 OF 11 HCPLUS COPYRIGHT 2003 ACS

AN 1994:164991 HCPLUS

DN 120:164991

TI Reductive Dehalogenation vs Substitution in the Polyetherification of Bis(aryl chloride)s Activated by Carbonyl Groups with Hydroquinones: A Potential Competition between SET and Polar Pathways

AU Percec, V.; Clough, R. S.; Rinaldi, P. L.; Litman, V., E.

CS Department of Macromolecular Science, Case Western Reserve University, Cleveland, OH, 44106, USA

SO Macromolecules (1994), 27(6), 1535-47

CODEN: MAMOBX; ISSN: 0024-9297

DT Journal
LA English
CC 35-3 (Chemistry of Synthetic High Polymers)
AB Arom. poly(ether ketones) are frequently synthesized by nucleophilic substitution of the halide of a bis(aryl halide) by a bisphenolate. The bis(aryl halide) is activated toward nucleophilic attack by a carbonyl group. When the bisphenol is hydroquinone, bis(aryl fluorides) afford high mol. wt. polymers, whereas bis(aryl chlorides) often yield low mol. wt. polymers. This paper demonstrates that bis(aryl chlorides) and hydroquinones can be condensed to produce high mol. wt. polymers. The ability to obtain high mol. wt. polymers from bis(aryl chlorides) is dependent on the structure of the bisphenolate and the reaction conditions. The mol. wt. that can be achieved in the polyetherification of bis(aryl chlorides) with hydroquinone or substituted hydroquinones can be limited by the occurrence of reductive dehalogenation. Reductive dehalogenation has not been obsd. in the condensation of bisphenolates which are weaker electron donors (i.e., have less neg. oxidn. potentials) than the dianion of hydroquinone, such as the bisphenolates of 4,4'-isopropylidenediphenol (Bisphenol A or BPA), 4,4'-oxydiphenol (ODP), 1,1-bis(2-methyl-4-hydroxy-5-tert-butylphenyl)ethane (MHBPE), etc., with bis(aryl chlorides) under identical conditions to those used in the polyetherifications involving the hydroquinones. These results strongly suggest that reductive dehalogenation is due to single electron transfer (SET) from the dianion of hydroquinone (or substituted hydroquinones) to the 4-chlorobenzophenone moiety. In many cases, the mol. wts. of the polymers synthesized from bis(aryl chlorides) and hydroquinones are not detd. by the reactivity of the monomers but by their selectivity. The factors that govern the selectivity between arom. nucleophilic substitution and reductive dehalogenation are discussed.
ST electron transfer chlorobenzophenone hydroquinone dianion; ketone bisaryl chloride polyetherification hydroquinone; mechanism bischloroaryl ketone polymn hydroquinone; reductive dehalogenation bischloroaryl ketone hydroquinone; substitution bischloroaryl ketone polymn hydroquinone
IT Kinetics of electron exchange
(between tert-butylhydroquinone dianion and chlorobenzophenone moiety, polyetherification mechanism in relation to)
IT Chains, chemical
(end-groups of, of arom. polyether-polyketones prep'd. by polyetherification, polymn. mechanism in relation to)
IT Electric potential
(oxidn., of tert-butylhydroquinone dianion, polyetherification of carbonyl group-activated bis(aryl halides) with hydroquinones in relation to)
IT Polyketones
RL: SPN (Synthetic preparation); PREP (Preparation)
(polyether-, arom., prepn. of, by polyetherification of bis(aryl halides) activated by carbonyl groups with hydroquinones, mechanism of)
IT Polyethers, preparation
RL: SPN (Synthetic preparation); PREP (Preparation)
(polyketone-, arom., prepn. of, by polyetherification of bis(aryl halides) activated by carbonyl groups with hydroquinones, mechanism of)
IT Electric potential
(redn., of chlorobenzophenone, polyetherification of bis(aryl halides) activated by carbonyl groups with hydroquinones in relation to)
IT Polymerization
(soln., of haloid-contg. arom. ketones with bisphenols, mechanism of, reductive dehalogenation vs. substitution in)
IT 2359-09-3P, 5-tert-Butylisophthalic acid

RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
 (prepn. and chlorination and benzoylation of)

IT 25897-65-8P, Bisphenol A-4,4'-difluorobenzophenone copolymer 41205-96-3P
 100344-02-3P 100344-94-3P 109521-12-2P 113736-28-0P, Bisphenol
 A-4,4'-dichlorobenzophenone copolymer 119799-53-0P 119822-48-9P,
 4,4'-Dichlorobenzophenone-2-tert-butyl-1,4-hydroquinone copolymer, SRU
 136116-09-1P 136116-10-4P, 4,4'-Dichlorobenzophenone-2-tert-butyl-1,4-
 hydroquinone copolymer 136116-11-5P 136327-54-3P 153366-69-9P
153366-70-2P 153366-71-3P 153366-72-4P 153366-73-5P
 153366-74-6P 153366-75-7P 153366-76-8P 153549-61-2P
 RL: SPN (Synthetic preparation); PREP (Preparation)
 (prepn. and mol. wt. and identification of chain termination groups of)

IT 632-52-0, Tetraphenylhydrazine
 RL: USES (Uses)
 (prepn. and polyetherification of bis(aryl chlorides)s activated by
 carbonyl groups with hydroquinones in presence of)

IT 1965-09-9P, Bis(4-hydroxyphenyl) ether 3772-18-7P, 1,1-Bis(2-methyl-4-
 hydroxy-5-tert-butylphenyl)ethane
 RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT
 (Reactant or reagent)
 (prepn. and polymn. of, with bis(aryl chlorides) activated by carbonyl
 groups, mechanism of, reductive dehalogenation vs. substitution in)

IT 22198-44-3P, Methanone, 1,3-phenylenebis[(4-chlorophenyl)- 108464-88-6P,
 Methanone, 1,3-phenylenebis[(4-fluorophenyl)- 153366-66-6P
 153366-67-7P
 RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT
 (Reactant or reagent)
 (prepn. and polymn. of, with hydroquinones, mechanism of, reductive
 dehalogenation vs. substitution in)

IT 153366-68-8P
 RL: SPN (Synthetic preparation); PREP (Preparation)
 (prepn. of, as model for arom. polyether-polyketones)

IT **153366-70-2P**
 RL: SPN (Synthetic preparation); PREP (Preparation)
 (prepn. and mol. wt. and identification of chain termination groups of)

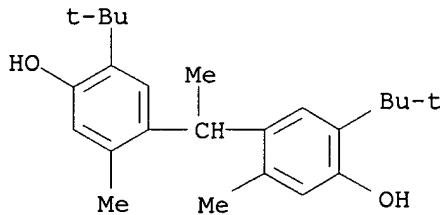
RN 153366-70-2 HCPLUS

CN Methanone, bis(4-chlorophenyl)-, polymer with 4,4'-ethylenebis[2-(1,1-
 dimethylethyl)-5-methylphenol] and 4,4'-(1-methylethyldene)bis[phenol]
 (9CI) (CA INDEX NAME)

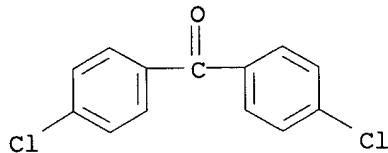
CM 1

CRN 3772-18-7

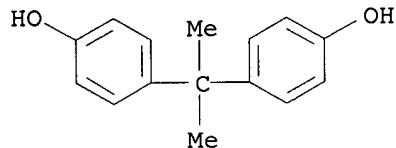
CMF C24 H34 O2



CM 2

CRN 90-98-2
CMF C13 H8 Cl2 O

CM 3

CRN 80-05-7
CMF C15 H16 O2

L10 ANSWER 7 OF 11 HCAPLUS COPYRIGHT 2003 ACS
 AN 1993:518114 HCAPLUS
 DN 119:118114
 TI Poly(aryl ether)/liquid crystalline polyester block copolymers and their production
 IN Kumpf, Robert J.; Wicks, Douglas A.; Nerger, Dittmar K.; Pielartzik, Harald; Wehrmann, Rolf
 PA Miles Inc., USA
 SO Can. Pat. Appl., 27 pp.
 CODEN: CPXXEB
 DT Patent
 LA English
 IC ICM C08G063-88
 ICS C09K019-38
 CC 35-5 (Chemistry of Synthetic High Polymers)
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	CA 2068286	AA	19921116	CA 1992-2068286	19920508
	US 5618889	A	19970408	US 1991-701425	19910515
PRAI	US 1991-701425		19910515		

AB The block copolymer is prep'd. by transesterification of an ester-contg. poly(aryl ether ketone) and a liq. cryst. polyester in presence or absence of a catalyst and in solvent or melt blend. Thus, a 0.0952:0.1:0.0048 (molar) bisphenol A-difluorobenzophenone-4-hydroxyphenyl 4-hydroxybenzoate copolymer and 0.181:0.289:0.0722:0.181:0.00728 (molar) tert-butylhydroquinone-chloroterephthaloyl chloride-isophthaloyl chloride-phenylhydroquinone-phenylphenol copolymer were heated to 275.degree. in presence of KOAc and PhCl under N, PhCl distd. off, the

mixt. cooled, dissolved in CH₂Cl₂, pptd. in MeOH and dried to give the block copolymer with wt.-av. mol. wt. 35,000, which formed an isotropic melt.

ST liq cryst block copolyester; polyether polyketone block polyester

IT Liquid crystals, polymeric
(block polyether-polyester-polyketones, prepn. and properties of)

IT Polymerization
(block, of ester-contg. poly(ether ketone) with liq. cryst. polyesters)

IT Polymerization catalysts
(block, potassium acetate, for transesterification of polyethers with liq. cryst polyesters)

IT Polysulfones, preparation
RL: RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(polyester-polyether-, arom., prepn. and block polymn. of, with liq. cryst. polyesters)

IT Polyketones
RL: SPN (Synthetic preparation); PREP (Preparation)
(polyester-polyether-, arom., block)

IT Polyethers, preparation
RL: SPN (Synthetic preparation); PREP (Preparation)
(polyester-polyketone-, arom., block)

IT Polyethers, preparation
RL: RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(polyester-polysulfone-, arom., prepn. and block polymn. of, with liq. cryst. polyesters)

IT Polyesters, preparation
RL: SPN (Synthetic preparation); PREP (Preparation)
(polyether-polyketone-, arom., block)

IT Polyesters, preparation
RL: RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(polyether-polysulfone-, arom., prepn. and block polymn. of, with liq. cryst. polyesters)

IT 149751-66-6
RL: RCT (Reactant); RACT (Reactant or reagent)
(liq. cryst., block polymn. of, with poly(ether ketones))

IT 137426-11-0P 149751-65-5P
RL: RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(prepn. and block polymn. of, with liq. cryst. polyesters)

IT 25897-65-8P 41205-96-3P
RL: PREP (Preparation)
(prepn. of)

IT **149751-67-7P**
RL: PREP (Preparation)
(prepn. of, from liq.-cryst. polyester and ester-contg. polyether polyketone)

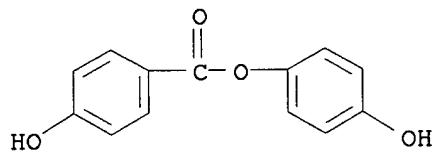
IT 127-08-2, Potassium acetate
RL: CAT (Catalyst use); USES (Uses)
(transesterification catalyst, for block polymn. of polyether-polyketones and liq. cryst. polyesters)

IT **149751-67-7P**
RL: PREP (Preparation)
(prepn. of, from liq.-cryst. polyester and ester-contg. polyether polyketone)

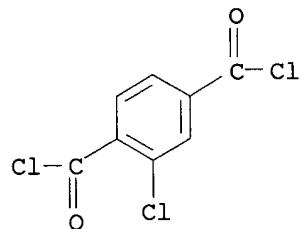
RN 149751-67-7 HCPLUS

CN 1,3-Benzenedicarbonyl dichloride, polymer with [1,1'-biphenyl]-2,5-diol, bis(4-fluorophenyl)methanone, 2-chloro-1,4-benzenedicarbonyl dichloride, 2-(1,1-dimethylethyl)-1,4-benzenediol, 4-hydroxyphenyl 4-hydroxybenzoate and 4,4'-(1-methylethylidene)bis[phenol], block (9CI) (CA INDEX NAME)

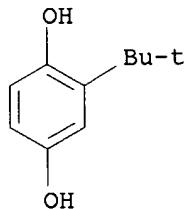
CM 1

CRN 28084-48-2
CMF C13 H10 O4

CM 2

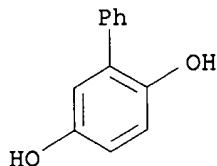
CRN 13815-87-7
CMF C8 H3 Cl3 O2

CM 3

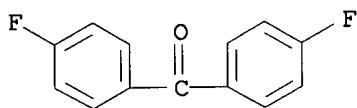
CRN 1948-33-0
CMF C10 H14 O2

CM 4

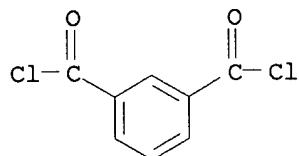
CRN 1079-21-6
CMF C12 H10 O2



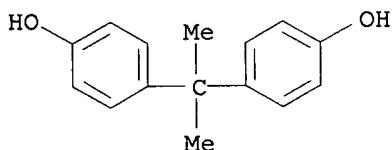
CM 5

CRN 345-92-6
CMF C13 H8 F2 O

CM 6

CRN 99-63-8
CMF C8 H4 Cl2 O2

CM 7

CRN 80-05-7
CMF C15 H16 O2

L10 ANSWER 8 OF 11 HCPLUS COPYRIGHT 2003 ACS

AN 1992:84290 HCPLUS

DN 116:84290

TI Synthesis and physical properties of soluble, amorphous poly(ether ketone)s containing the o-dibenzoylbenzene moiety

AU Singh, Rina; Hay, Allan S.

CS Dep. Chem., McGill Univ., Montreal, QC, H3A 2K6, Can.
 SO Macromolecules (1992), 25(3), 1017-24
 CODEN: MAMOBX; ISSN: 0024-9297
 DT Journal
 LA English
 CC 35-5 (Chemistry of Synthetic High Polymers)
 AB Fluoro monomers contg. 1,2-dibenzoylbenzene moiety were prepd. in very high yields. These fluoro monomers polymd. with bisphenols in the presence of excess anhyd. K₂CO₃ in MeCONMe₂ to give high-mol.-wt. amorphous poly(aryl ether ketones) which are very sol. in solvents such as CHCl₃ and PhMe at room temp., have glass transition temps. 160-313.degree., and are easily cast into flexible, colorless and transparent films. The 5% wt. losses by thermogravimetric anal. for these materials were all >500.degree..
 ST dibenzoylbenzene contg fluoro monomer; polyether polyketone
 dibenzoylbenzene contg; glass temp polyether polyketone dibenzoylbenzene
 IT Glass temperature and transition
 (of arom. polyether-polyketones contg. dibenzoylbenzene group)
 IT Polyketones
 RL: SPN (Synthetic preparation); PREP (Preparation)
 (polyether-, arom., dibenzoylbenzene group-contg., prepn. and characterization of)
 IT Polyketones
 RL: SPN (Synthetic preparation); PREP (Preparation)
 (polyether-, arom., dibenzoylbenzene group-contg., reaction products, with di-tert-butylphenol, prepn. and characterization of)
 IT Polyethers, preparation
 RL: SPN (Synthetic preparation); PREP (Preparation)
 (polyketone-, arom., dibenzoylbenzene group-contg., prepn. and characterization of)
 IT Polyethers, compounds
 RL: SPN (Synthetic preparation); PREP (Preparation)
 (polyketone-, arom., dibenzoylbenzene group-contg., reaction products, with di-tert-butylphenol, prepn. and characterization of)
 IT 1138-52-9DP, 3,5-Di-tert-butylphenol, reaction products with arom. polyether-polyketones 132980-73-5DP, reaction products with di-tert-butylphenol 132980-73-5P 132980-74-6DP, reaction products with di-tert-butylphenol 132980-74-6P 132980-75-7DP, reaction products with di-tert-butylphenol 132980-75-7P 132980-78-0P 132980-79-1P
 132980-80-4P **138181-12-1P 138181-13-2P** 138181-19-8P
 138181-20-1P 138181-21-2P 138181-22-3P 138181-23-4P 138181-24-5P
 138181-31-4P 138181-32-5P 138181-33-6P 138181-34-7P 138181-35-8P
 138181-36-9P 138181-37-0P 138181-43-8P 138181-44-9P 138234-73-8P
138234-74-9P
 RL: SPN (Synthetic preparation); PREP (Preparation)
 (prepn. and characterization of)
 IT 132980-72-4P
 RL: SPN (Synthetic preparation); PREP (Preparation)
 (prepn. and conversion of)
 IT 132980-68-8P, 1,3-Bis(4-fluorophenyl)-4,7-dihydroisobenzofuran
 RL: SPN (Synthetic preparation); PREP (Preparation)
 (prepn. and conversion of, to bis(fluorobenzoyl)benzene)
 IT 132980-69-9P, 1,3-Bis(4-fluorophenyl)-4,7-dihydro-4,7-diphenylisobenzofuran
 RL: SPN (Synthetic preparation); PREP (Preparation)
 (prepn. and conversion of, to bis(fluorobenzoyl)diphenylbenzene)
 IT 132980-64-4P, 1,2-Bis(4-fluorobenzoyl)-3,6-diphenylbenzene 132980-70-2P,
 1,2-Bis(4-fluorobenzoyl)benzene 132980-71-3P, 1,2-Bis(4-fluorobenzoyl)-

3,4,5,6-tetraphenylbenzene
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(prepn. and polymn. of, with bisphenols)

IT 138234-72-7P
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(prepn. and reaction of, with butadiene)

IT 133039-85-7P, 1,2-Bis(4-fluorobenzoyl)acetylene
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(prepn. and reaction of, with tetraphenylcyclopentadienone)

IT 132980-66-6P, 4,5-Bis(4-fluorobenzoyl)cyclohexene 132980-67-7P,
1,2-Bis(4-fluorobenzoyl)-3,6-diphenylcyclohex-4-ene
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(prepn. and rearrangement of)

IT 479-33-4, Tetraphenylcyclopentadienone
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with bis(fluorobenzoyl)acetylene)

IT 106-99-0, 1,3-Butadiene, reactions 538-81-8, trans,trans-1,4-Diphenyl-1,3-butadiene
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with bis(fluorobenzoyl)ethylene)

IT 627-63-4, Fumaryl chloride
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with fluorobenzene)

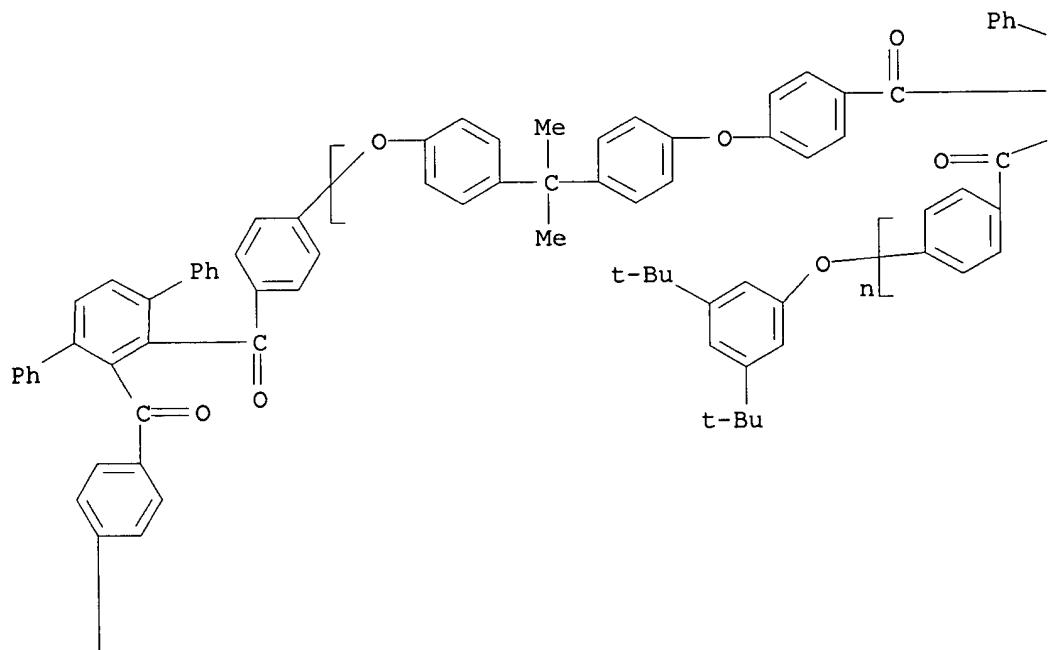
IT 462-06-6, Fluorobenzene
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with fumaryl chloride)

IT 138181-12-1P 138181-13-2P 138234-74-9P
RL: SPN (Synthetic preparation); PREP (Preparation)
(prepn. and characterization of)

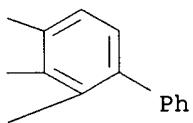
RN 138181-12-1 HCAPLUS

CN Poly[oxy-1,4-phenylene(1-methylethyldene)-1,4-phenyleneoxy-1,4-phenylene carbonyl[1,1':4',1''-terphenyl]-2',3'-diylcarbonyl-1,4-phenylene], .alpha.-[4-[[3'-[4-[3,5-bis(1,1-dimethylethyl)phenoxy]benzoyl][1,1':4',1''-terphenyl]-2'-yl]carbonyl]phenyl]-.omega.-[3,5-bis(1,1-dimethylethyl)phenoxy]- (9CI) (CA INDEX NAME)

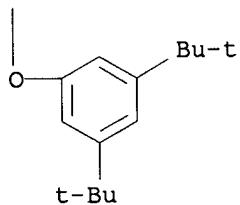
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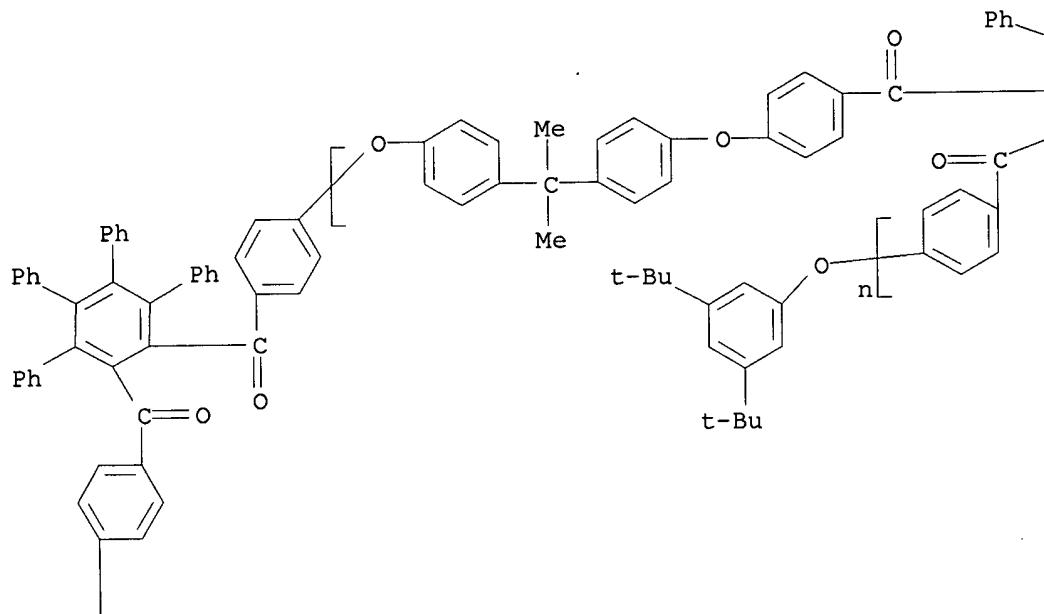
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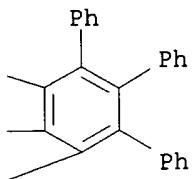
RN 138181-13-2 HCPLUS

CN Poly[oxy-1,4-phenylene(1-methylethylidene)-1,4-phenyleneoxy-1,4-phenylene carbonyl(5',6'-diphenyl[1,1':2',1''-terphenyl]-3',4'-diyl) carbonyl-1,4-phenylene], .alpha.-[4-[[4-[[4-[3,5-bis(1,1-dimethylethyl)phenoxy]benzoyl]-5',6'-diphenyl[1,1':2',1''-terphenyl]-3'-yl]carbonyl]phenyl]-.omega.-[3,5-bis(1,1-dimethylethyl)phenoxy]- (9CI) (CA INDEX NAME)

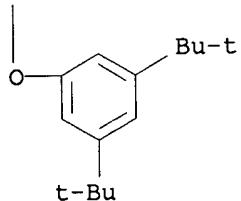
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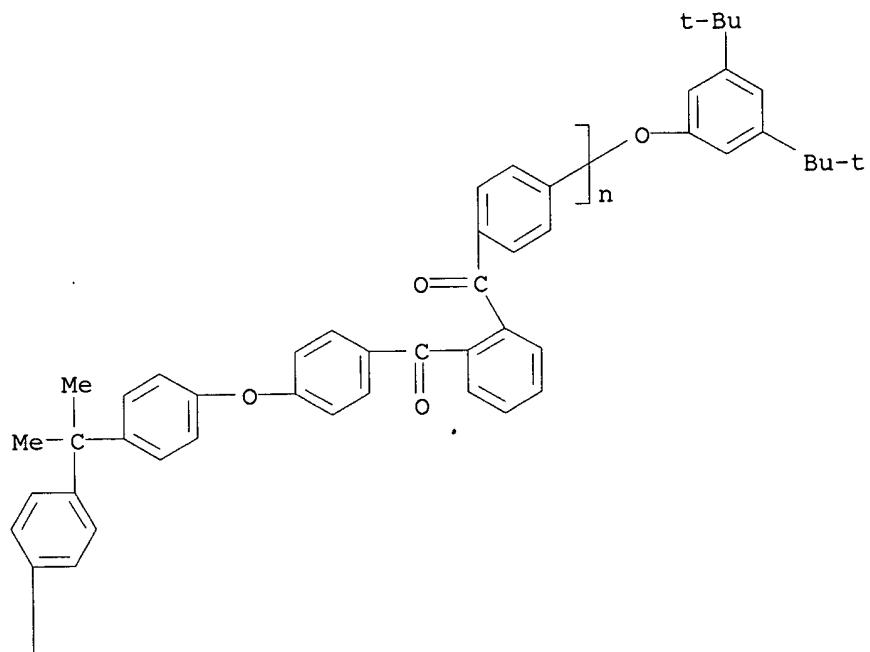


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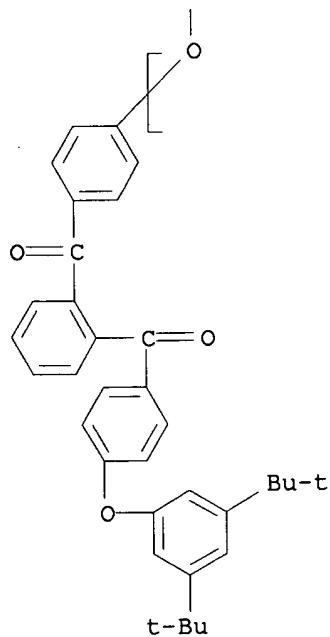


RN 138234-74-9 HCPLUS
 CN Poly[oxy-1,4-phenylene(1-methylethylidene)-1,4-phenyleneoxy-1,4-phenylene carbonyl-1,2-phenylene carbonyl-1,4-phenylene],
 .alpha.-[4-[2-[4-[3,5-bis(1,1-dimethylethyl)phenoxy]benzoyl]benzoyl]phenyl
].-omega.-[3,5-bis(1,1-dimethylethyl)phenoxy]- (9CI) (CA INDEX NAME)

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L10 ANSWER 9 OF 11 HCAPLUS COPYRIGHT 2003 ACS
AN 1992:60139 HCAPLUS

KATHLEEN FULLER EIC 1700/PARKER LAW 308-4290

DN 116:60139
TI Synthesis and physical properties of amorphous poly(aryl ether isoquinolines)
AU Singh, Rina; Hay, Allan S.
CS Dep. Chem., McGill Univ., Montreal, QC, H3A 2K6, Can.
SO Macromolecules (1992), 25(3), 1033-40
CODEN: MAMOBX; ISSN: 0024-9297
DT Journal
LA English
CC 35-7 (Chemistry of Synthetic High Polymers)
AB The prepn. of poly(aryl ether isoquinolines) was described via an intramol. ring-closure reaction of poly(aryl ether ketones) contg. the o-dibenzoylbenzene moiety with benzylamine in the presence of 1,8-diazabicyclo[5.4.0]undecene in refluxing ClPh. The prepn. of copolymers of poly(aryl ether ketones) and poly(aryl ether isoquinolines) was demonstrated and the copolymer contents were detd. by ¹H NMR studies. Ring-closure reactions of previously prep'd. end-capped poly(aryl ether ketones) to poly(aryl ether isoquinolines) were done to det. exact mol. wts. of the resulting polymers. Various fluoro-substituted isoquinoline monomers were prep'd. and polymd. with bisphenols in N-methylcaprolactam in the presence of excess K₂CO₃. The high-mol.-wt. polymers showed glass temp. 225-320.degree.. Studies by TGA showed polymer 5% wt. losses in air and N at >500.degree..
ST arom polyether isoquinoline prepn property; glass temp arom polyether isoquinoline; polyketone polyether reaction benzylamine; bisphenol polymn fluoro substituted isoquinoline
IT Glass temperature and transition
 (of arom. poly(ether isoquinolines))
IT Permeability and Permeation
 (of oxygen, through arom. poly(ether isoquinolines))
IT Polyethers, preparation
 RL: SPN (Synthetic preparation); PREP (Preparation)
 (arom., isoquinoline group-contg., prepn. and properties of)
IT 7782-44-7, Oxygen, properties
 RL: PRP (Properties)
 (permeation of, through arom. poly(ether isoquinolines))
IT 138181-05-2P 138181-06-3P 138181-07-4P
 RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
 (prepn. and polymn. of, with bisphenols)
IT 100-46-9DP, Benzylamine, reaction products with arom. polyether-polyketones contg. dibenzoylbenzene group 105451-78-3DP, reaction products with benzylamine 132100-40-4DP, reaction products with benzylamine 132980-74-6DP, reaction products with benzylamine 132980-75-7DP, reaction products with benzylamine 132980-78-0DP, reaction products with benzylamine 132980-79-1DP, reaction products with benzylamine 132980-80-4DP, reaction products with benzylamine 138181-11-0DP, reaction products with benzylamine 138181-12-1DP, reaction products with benzylamine 138181-13-2DP, reaction products with benzylamine 138181-14-3P 138181-15-4P 138181-16-5P 138181-17-6P 138181-18-7P 138181-19-8DP, reaction products with benzylamine 138181-20-1DP, reaction products with benzylamine 138181-21-2DP, reaction products with benzylamine 138181-23-4DP, reaction products with benzylamine 138181-22-3DP, reaction products with benzylamine 138181-24-5DP, reaction products with benzylamine 138181-33-6DP, reaction products with benzylamine 138181-34-7DP, reaction products with benzylamine 138181-35-8DP, reaction products with benzylamine 138181-36-9DP, reaction products with benzylamine

benzylamine 138181-37-0DP, reaction products with benzylamine
 138181-38-1P 138181-39-2P 138181-40-5P 138181-41-6P 138181-42-7P
 RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)
 (prepn. and properties of)

IT 132980-64-4 132980-70-2 132980-71-3
 RL: RCT (Reactant); RACT (Reactant or reagent)
 (reaction of, with benzylamine)

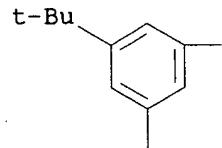
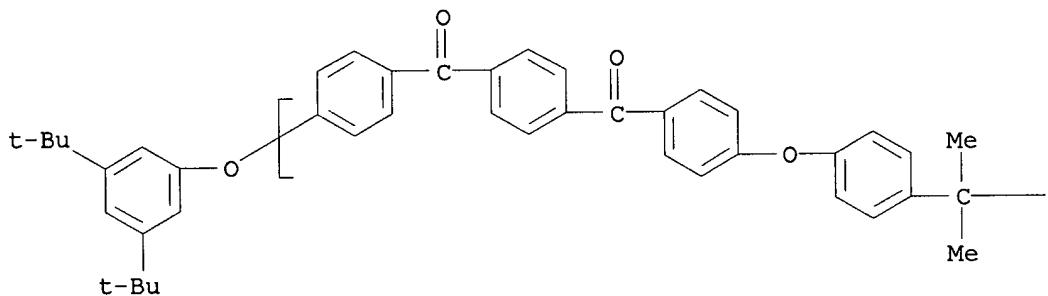
IT 100-46-9, Benzylamine, reactions
 RL: RCT (Reactant); RACT (Reactant or reagent)
 (reaction of, with bis(fluorobenzoyl)benzenes)

IT 138181-11-0DP, reaction products with benzylamine
 138181-12-1DP, reaction products with benzylamine
 138181-13-2DP, reaction products with benzylamine
 RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)
 (prepn. and properties of)

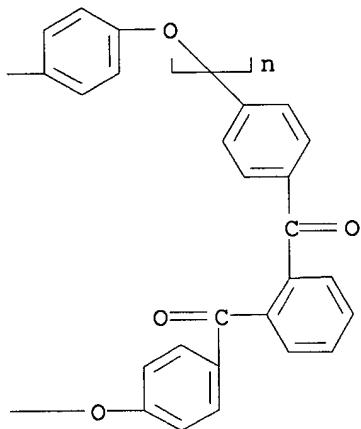
RN 138181-11-0 HCAPLUS

CN Poly[oxy-1,4-phenylene(1-methylethyldene)-1,4-phenyleneoxy-1,4-phenylene carbonyl-1,4-phenylene carbonyl-1,4-phenylene],
 .alpha.-[4-[2-[4-[3,5-bis(1,1-dimethylethyl)phenoxy]benzoyl]benzoyl]phenyl
].omega.-[3,5-bis(1,1-dimethylethyl)phenoxy]- (9CI) (CA INDEX NAME)

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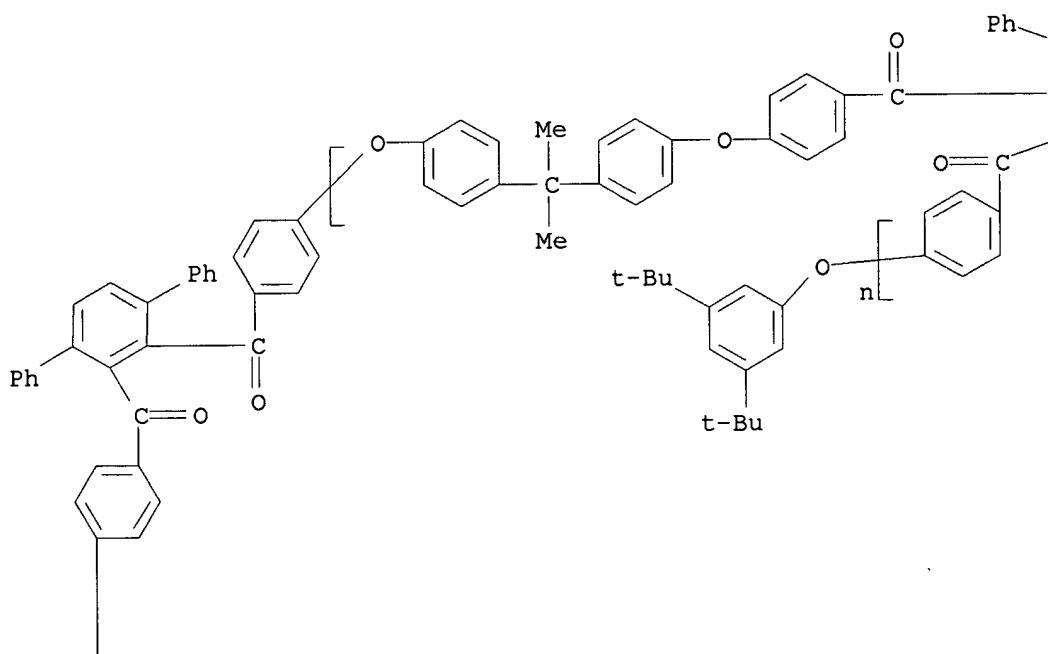


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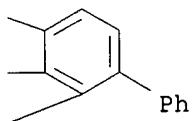
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RN 138181-12-1 HCAPLUS
CN Poly[oxy-1,4-phenylene(1-methylethylidene)-1,4-phenyleneoxy-1,4-phenylene carbonyl[1,1':4',1''-terphenyl]-2',3'-diyl carbonyl-1,4-phenylene], .alpha.-[4-[[3'-[4-[3,5-bis(1,1-dimethylethyl)phenoxy]benzoyl]-[1,1':4',1''-terphenyl]-2'-yl]carbonyl]phenyl]-.omega.-[3,5-bis(1,1-dimethylethyl)phenoxy]- (9CI) (CA INDEX NAME)

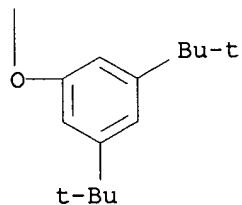
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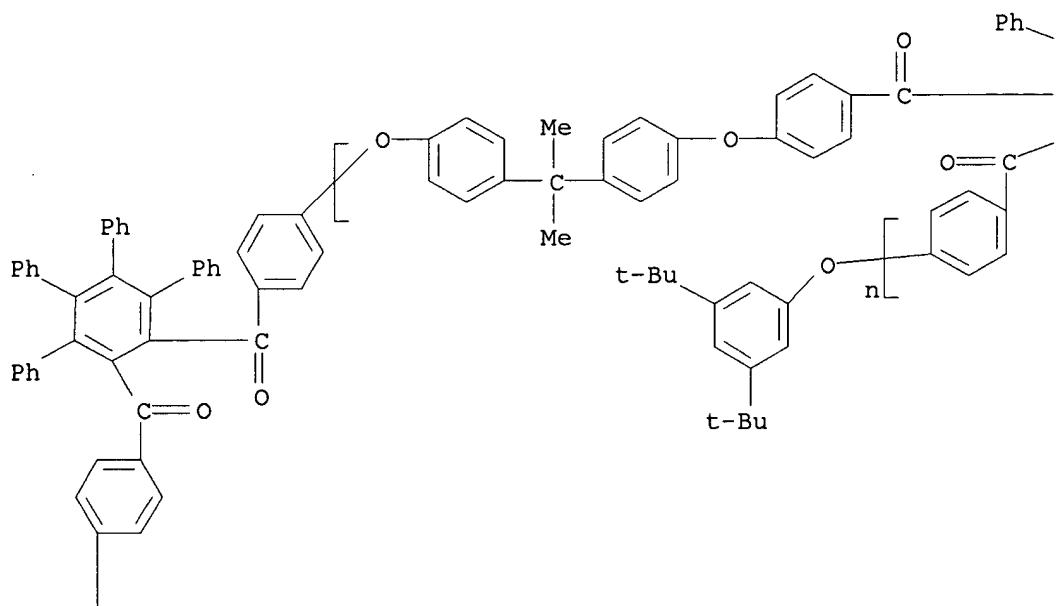
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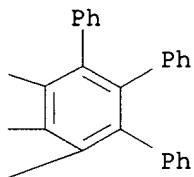
RN 138181-13-2 HCAPLUS

Poly[oxy-1,4-phenylene(1-methylethylidene)-1,4-phenyleneoxy-1,4-phenylene carbonyl(5',6'-diphenyl[1,1':2',1''-terphenyl]-3',4'-diyl)carbonyl-1,4-phenylene], .alpha.-[4-[[4'-[4-[3,5-bis(1,1-dimethylethyl)phenoxy]benzoyl]-5',6'-diphenyl[1,1':2',1''-terphenyl]-3'-yl]carbonyl]phenyl]-.omega.-[3,5-bis(1,1-dimethylethyl)phenoxy]- (9CI) (CA INDEX NAME)

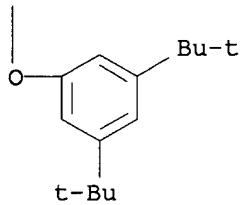
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PAGE 2-A



L10 ANSWER 10 OF 11 HCPLUS COPYRIGHT 2003 ACS
 AN 1992:60138 HCPLUS
 DN 116:60138
 TI Synthesis and physical properties of poly(aryl ether phthalazine)s
 AU Singh, Rina; Hay, Allan S.
 CS Dep. Chem., McGill Univ., Montreal, QC, H3A 2K6, Can.
 SO Macromolecules (1992), 25(3), 1025-32

CODEN: MAMOBX; ISSN: 0024-9297

DT Journal

LA English

CC 35-7 (Chemistry of Synthetic High Polymers)

AB The synthesis of poly(aryl ether phthalazines) is described via an intramol. ring-closure reaction of poly(aryl ether ketones) contg. the o-dibenzoylbenzene moiety with hydrazine monohydrate. The synthesis of copolymers of poly(aryl ether ketones) and poly(aryl ether phthalazines) was demonstrated and the copolymer ratios were detd. by 1H NMR studies. Various fluoro-substituted phthalazine monomers were prep'd. and polym'd. with bisphenols in N-methyl-2-pyrrolidinone in the presence of excess K₂CO₃. High-mol.-wt. polymers were obtained with glass transition temps. 235-340.degree.. Thermal stabilities for the resulting materials by TGA showed polymer decompr. temps. (5% wt. loss) in air and in nitrogen ranging 460-535.degree.. The polymn. of 3,6-bis(4-fluorophenyl)pyridazine with 4,4'-(1-methylethylidene)bisphenol also afforded a new class of polymers, the poly(aryl ether pyridazines).

ST arom polyether phthalazine prepn property; glass temp arom polyether phthalazine; hydrazine monohydrate reaction polyether polyketone; bisfluorophenylpyridazine polymn bisphenol

IT Glass temperature and transition

(of arom. poly(ether phthalazines))

IT Permeability and Permeation

(of oxygen, through arom. poly(ether phthalazines))

IT Polyethers, preparation

RL: SPN (Synthetic preparation); PREP (Preparation)
(arom., phthalazine group-contg., prepn. and properties of)

IT 7782-44-7, Oxygen, properties

RL: PRP (Properties)
(permeation of, through arom. poly(ether phthalazines))

IT 138181-10-9P

RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)

(prepn. and polymn. of, with bisphenol A)

IT 132980-65-5P 138181-08-5P 138181-09-6P

RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)

(prepn. and polymn. of, with bisphenols)

IT 7803-57-8DP, Hydrazine monohydrate, reaction products with arom. polyether-polyketones 105451-78-3DP, reaction products with hydrazine monohydrate 132100-40-4DP, reaction products with hydrazine monohydrate

132980-74-6DP, reaction products with hydrazine monohydrate

132980-75-7DP, reaction products with hydrazine monohydrate

132980-78-0DP, reaction products with hydrazine monohydrate

132980-79-1DP, reaction products with hydrazine monohydrate

132980-80-4DP, reaction products with hydrazine monohydrate

138181-11-0DP, reaction products with hydrazine monohydrate

138181-12-1DP, reaction products with hydrazine monohydrate

138181-13-2DP, reaction products with hydrazine monohydrate

138181-19-8DP, reaction products with hydrazine monohydrate

138181-20-1DP, reaction products with hydrazine monohydrate

138181-21-2DP, reaction products with hydrazine monohydrate

138181-22-3DP, reaction products with hydrazine monohydrate

138181-23-4DP, reaction products with hydrazine monohydrate

138181-24-5DP, reaction products with hydrazine monohydrate

138181-25-6P

138181-26-7P 138181-27-8P 138181-28-9P 138181-29-0P

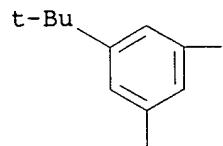
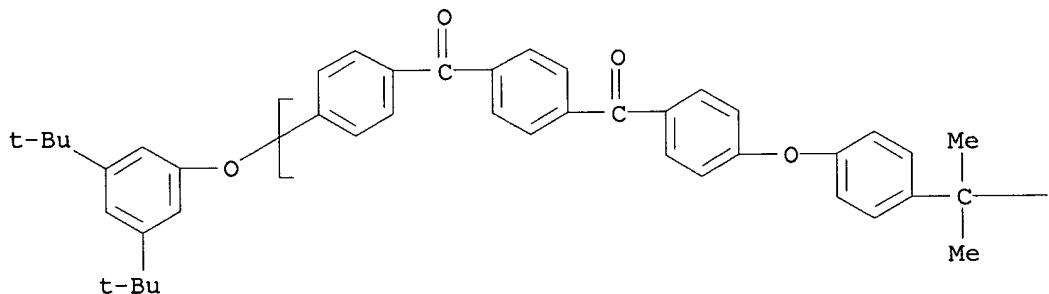
138181-30-3P

138181-31-4DP, reaction products with hydrazine monohydrate

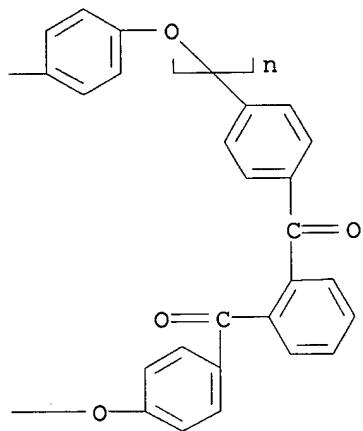
138181-32-5DP, reaction products with hydrazine monohydrate

138181-33-6DP, reaction products with hydrazine monohydrate
 138181-34-7DP, reaction products with hydrazine monohydrate
 138181-35-8DP, reaction products with hydrazine monohydrate
 138181-36-9DP, reaction products with hydrazine monohydrate
 138181-37-0DP, reaction products with hydrazine monohydrate
 138181-43-8DP, reaction products with hydrazine monohydrate
 138181-44-9DP, reaction products with hydrazine monohydrate 138181-46-1P
 138181-47-2P 138181-48-3P 138181-50-7P 138181-52-9P 138181-53-0P
 RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)
 (prepn. and properties of)
 IT 7803-57-8, Hydrazine monohydrate
 RL: RCT (Reactant); RACT (Reactant or reagent)
 (reaction of, with bis(fluorobenzoyl)benzene)
 IT 25650-13-9 132980-64-4 132980-70-2 132980-71-3
 RL: RCT (Reactant); RACT (Reactant or reagent)
 (reaction of, with hydrazine monohydrate)
 IT 138181-11-0DP, reaction products with hydrazine monohydrate
 138181-12-1DP, reaction products with hydrazine monohydrate
 138181-13-2DP, reaction products with hydrazine monohydrate
 RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)
 (prepn. and properties of)
 RN 138181-11-0 HCPLUS
 CN Poly[oxy-1,4-phenylene(1-methylethylidene)-1,4-phenyleneoxy-1,4-phenylene carbonyl-1,4-phenylene carbonyl-1,4-phenylene],
 .alpha.-[4-[2-[4-[3,5-bis(1,1-dimethylethyl)phenoxy]benzoyl]benzoyl]phenyl
].omega.-[3,5-bis(1,1-dimethylethyl)phenoxy]- (9CI) (CA INDEX NAME)

PAGE 1-A



PAGE 1-B



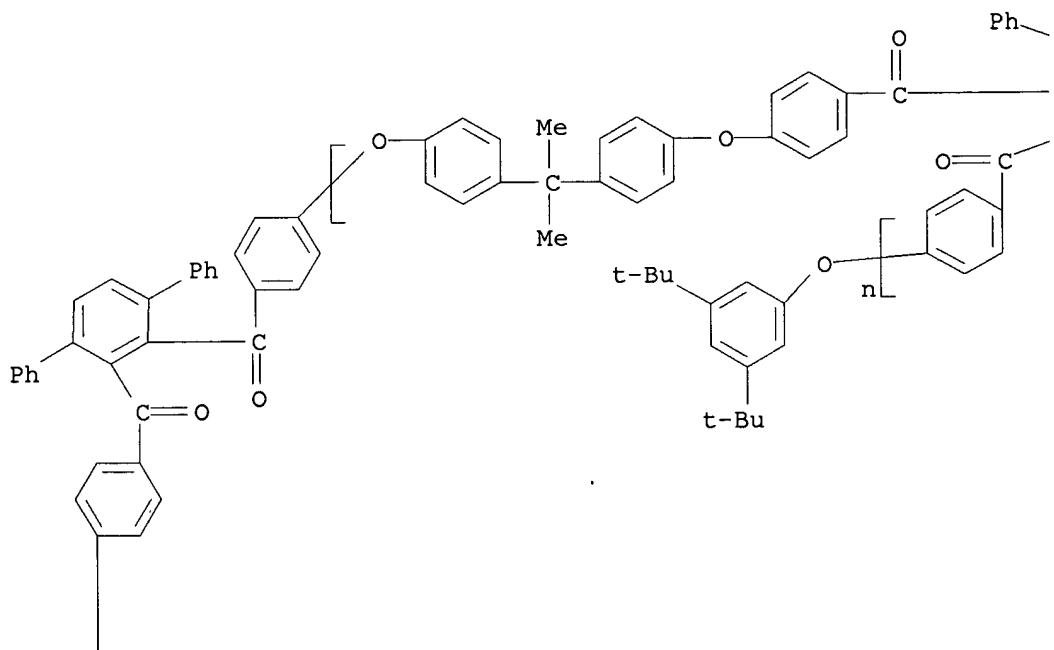
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|
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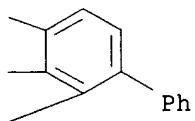
RN 138181-12-1 HCPLUS

CN Poly[oxy-1,4-phenylene(1-methylethylidene)-1,4-phenyleneoxy-1,4-phenylene carbonyl[1,1':4',1''-terphenyl]-2',3'-diyl carbonyl-1,4-phenylene], .alpha.-[4-[[3'-[4-[3,5-bis(1,1-dimethylethyl)phenoxy]benzoyl][1,1':4',1''-terphenyl]-2'-yl]carbonyl]phenyl]-.omega.-[3,5-bis(1,1-dimethylethyl)phenoxy]- (9CI) (CA INDEX NAME)

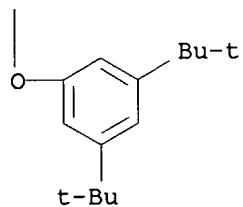
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PAGE 1-B



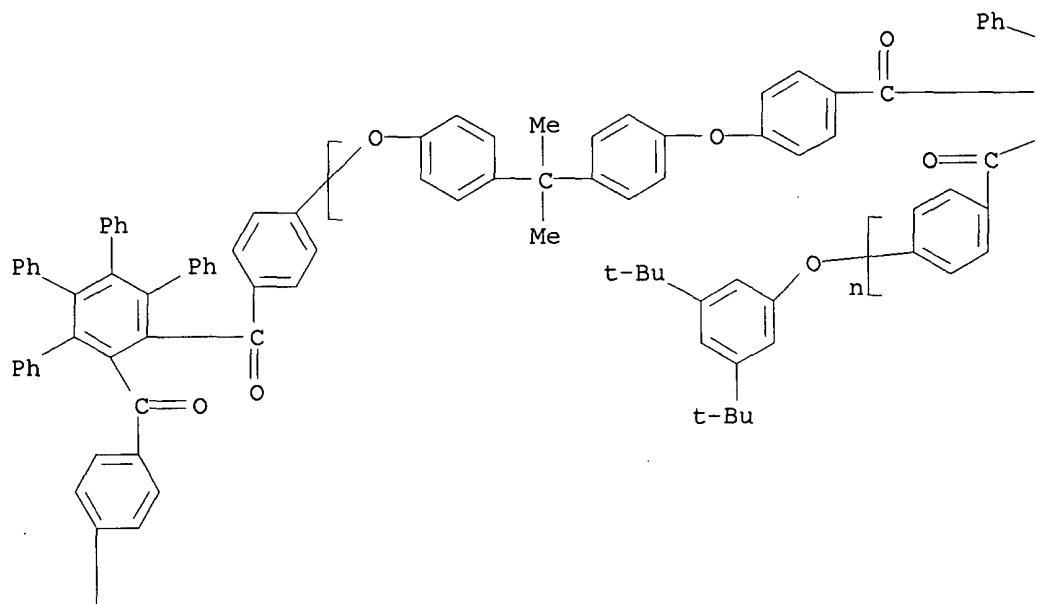
PAGE 2-A



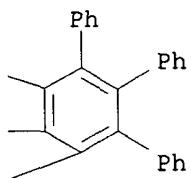
RN 138181-13-2 HCAPLUS

CN Poly[oxy-1,4-phenylene(1-methylethylidene)-1,4-phenyleneoxy-1,4-phenylene carbonyl(5',6'-diphenyl[1,1':2',1''-terphenyl]-3',4'-diyl) carbonyl-1,4-phenylene], .alpha.-[4-[[4'-[4-[3,5-bis(1,1-dimethylethyl)phenoxy]benzoyl]-5',6'-diphenyl[1,1':2',1''-terphenyl]-3'-yl]carbonyl]phenyl]-.omega.-[3,5-bis(1,1-dimethylethyl)phenoxy]- (9CI) (CA INDEX NAME)

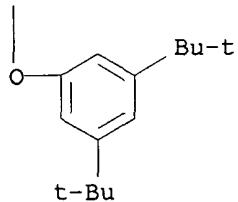
PAGE 1-A



PAGE 1-B



PAGE 2-A



L10 ANSWER 11 OF 11 HCPLUS COPYRIGHT 2003 ACS
 AN 1967:403646 HCPLUS
 DN 67:3646
 TI Fiber-forming condensation polyesters having enhanced resistance to photodegradation
 IN Maerov, Sidney B.
 PA du Pont de Nemours, E. I., and Co.

SO U.S., 9 pp.
CODEN: USXXAM

DT Patent
LA English
NCL 260047000
CC 39 (Textiles)

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 3308095		19670307	US	19610131
GI	For diagram(s), see printed CA Issue.				
AB	<p>Linear, fiber-forming condensation polyesters having enhanced uv light stability were prep'd. by condensing bifunctional, ester-forming monomers free of ethylenic unsatn. with 0.1-10 mole % of uv absorbing, ester-linking trihydroxybenzophenones or 2-benzamidophenyl-2H-benzotriazoles. Thus, a reaction mixt. contg. an equal no. of moles of 2,2-bis(4-hydroxyphenyl)propane diacetate and isophthalic acid and 3 mole % of the 2,4- and 2',4-diacetates of 2,2',4-trihydroxybenzophenone (I) was heated to 245.degree. and the temp. was increased to 300.degree. as the HOAc was distd. The pressure was reduced to 1.0 mm. and the polymn. was continued for 2 hrs. No trihydroxybenzophenone could be extd. from the polymer which m. 270.degree. and had an inherent viscosity of 0.50. A yarn, melt spun from the polymer, showed a light discoloration after 24 hrs. exposure to uv radiation while a similar yarn prep'd. without I discolored after 2 hrs. exposure. Other modifying agents used were 2,2',4-trihydroxy - 5 - tert - butylbenzophenone, 2-(3',5'-dicarboxybenzamido-2-phenyl)-2H-benzotriazole, 2-(3',5'-dicarbomethoxybenzamido-2-phenyl)-2H-benzotriazole, 2,2'-dihydroxy-4,4'-bis(.beta.-hydroxyethoxy)benzophenone, 2-(3',5'-dicarboxybenzenesulfonamido-2-phenyl)-2H-benzotriazole (II), and 2,2'-dihydroxy-4,4'-dicarboxymethoxybenzophenone. The compds. were also incorporated into poly(ethylene terephthalate) and 2,6-naphthalic acid-ethylene glycol polyesters.</p>				
ST	POLYESTERS LIGHT STABLE; BENZOTRIAZOLES UV ABSORBENTS; UV ABSORBENTS BENZOTRIAZOLES; TRIHYDROXYBENZOPHENONES UV ABSORBENTS; BENZOPHENONES UV ABSORBENTS; LIGHT STABLE POLYESTERS				
IT	<p>Fiber, polyester, preparation RL: PREP (Preparation) (2-benzamidophenyl-2H-benzotriazole or trihydroxybenzophenone copolymers for uv light-stable)</p>				
IT	Light, ultraviolet, chemical and physical effects (stabilizers, trihydroxybenzophenone polyesters, for fibers)				
IT	<p>Benzophenone, 2,2',4-trihydroxy-, derivs., polyesters Benzophenone, 2,4,4'-trihydroxy-, derivs., polyesters RL: USES (Uses) (for uv light-stable fibers)</p>				
IT	<p>30977-36-7P RL: PREP (Preparation) (manuf. of and uv light-stable films therefrom)</p>				
IT	<p>30977-31-2P RL: PREP (Preparation) (manuf. of, and uv light-stable fibers therefrom)</p>				
IT	<p>30977-46-9P 30977-47-0P RL: PREP (Preparation) (manuf. of, and uv light-stable films)</p>				
IT	<p>30977-36-7P 30977-44-7P 30977-45-8P RL: PREP (Preparation) (manuf. of, and uv light-stable films therefrom)</p>				

IT 30977-44-7P
 RL: PREP (Preparation)
 (manuf. of, and uv light-stable films thereof)

IT 30977-32-3P 30977-35-6P 30977-43-6P
 RL: PREP (Preparation)
 (manuf. of, for uv light-stable fibers)

IT 30977-28-7P 30977-37-8P 30977-46-9P 30977-47-0P 30977-48-1P
 RL: PREP (Preparation)
 (manuf. of, for uv light-stable films)

IT 30977-45-8P 30977-47-0P
 RL: IMF (Industrial manufacture); PREP (Preparation)
 (prepn. of)

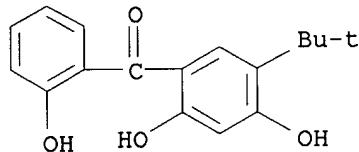
IT 30977-36-7P
 RL: PREP (Preparation)
 (manuf. of and uv light-stable films therefrom)

RN 30977-36-7 HCAPLUS

CN Isophthalic acid, polyester with 5-tert-butyl-2,2',4'-trihydroxybenzophenone and 4,4'-isopropylidenediphenol (8CI) (CA INDEX NAME)

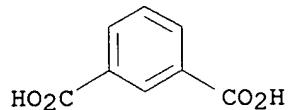
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CRN 15167-70-1
 CMF C17 H18 O4



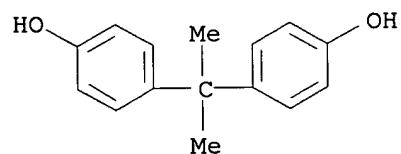
CM 2

CRN 121-91-5
 CMF C8 H6 O4



CM 3

CRN 80-05-7
 CMF C15 H16 O2



RL: PREP (Preparation)
(manuf. of, and uv light-stable films therefrom

=> **file pnttext**

COST IN U.S. DOLLARS
FULL ESTIMATED COST

SINCE FILE
ENTRY
0.21

TOTAL
SESSION
0.21

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FILE 'USPAT2' ENTERED AT 13:19:01 ON 21 APR 2003
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> **s Bender, Timothy P./in**

L1 0 BENDER, TIMOTHY P./IN

=> **s polyarylene ether# and solvent# and (difluorobenzophenone or difluoro-benzopheno**
L2 86 POLYARYLENE ETHER# AND SOLVENT# AND (DIFLUOROBENZOPHENONE OR
DIFLUORO-BENZOPHENONE)

=> **s 12 and (dimethylacetamide or sulfolane or dimethyl formamide or dimethyl sulfoxide)**
L3 72 L2 AND (DIMETHYLACETAMIDE OR SULFOLANE OR DIMETHYL FORMAMIDE
OR DIMETHYL SULFOXIDE OR METHYL PYRROLIDINONE OR HEXAMETHYLPHOSPHORIC TRAMIDE)

=> **s 13 and (potassium carbonate or cesium carbonate)**
L4 71 L3 AND (POTASSIUM CARBONATE OR CESIUM CARBONATE)

=> **s 14 and heat? and water**
L5 71 L4 AND HEAT? AND WATER

=> **s 1;5 and reflux**
L6 3 FILES SEARCHED...
2196677 L

5 IS NOT A RECOGNIZED COMMAND

The previous command name entered was not recognized by the system.
For a list of commands available to you in the current file, enter
"HELP COMMANDS" at an arrow prompt (=>).

=> **s 15 and reflux**
L7 55 L5 AND REFLUX

=> **s 12 and (dimethylacetamide or dimethyl acetamide) and (potassium carbonate or cesium carbonate)**
L8 70 L2 AND (DIMETHYLACETAMIDE OR DIMETHYL ACETAMIDE) AND (POTASSIUM CARBONATE OR CESIUM CARBONATE)

=> **d 17 1-55**

L7 ANSWER 1 OF 55 EUROPATFULL COPYRIGHT 2003 WILA
Full Text

PATENT APPLICATION - PATENTANMELDUNG - DEMANDE DE BREVET

AN 1117102 EUROPATFULL ED 20010730 EW 200129 FS OS

TIEN Method of manufacturing material for forming insulating film.
 TIDE Verfahren zur Herstellung von Material zur Herstellung von isolierenden Filmen.
 TIFR Procede de fabrication de materiaux pour la fabrication de films isolants.
 IN Suzuki, Hidenori, 11-301, Shoufu, 1, Morigayama-cho, Yokkaichi, Mie, JP; Kakinoki, Katsuyuki, 12-208, 1, Morigayama-cho, Yokkaichi, Mie, JP; Nakase, Yoshihisa, 317, Uninaka, Meiwa, Taki Gun, Mie, JP; Nishikawa, Michinori, 2-6-1-401, Umezono, Tsukuba, Ibaraki, JP; Okada, Takashi, 2-15-12-501, Umezono, Tsukuba, Ibaraki, JP; Yamada, Kinji, 2-18-33-M1-2, Umezono, Tsukuba, Ibaraki, JP
 PA JSR Corporation, 11-24, Tsukiji 2-chome, Chuo-ku, Tokyo, JP
 SO Wila-EPZ-2001-H29-T2b
 DS R AT; R BE; R CH; R CY; R DE; R DK; R ES; R FI; R FR; R GB; R GR; R IE; R IT; R LI; R LU; R MC; R NL; R PT; R SE; R TR; R AL; R LT; R LV; R MK; R RO; R SI
 PIT EPA2 EUROPÆISCHE PATENTANMELDUNG
 PI EP 1117102 A2 20010718
 OD 20010718
 AI EP 2001-100925 20010116
 PRAI JP 2000-2000007385 20000117
JP 2000-2000175684 20000612
 IC ICM H01B003-46
 ICS H01B003-42 C08G085-00 C08G077-34

L7 ANSWER 2 OF 55 EUROPATFULL COPYRIGHT 2003 WILA

Full
Text

PATENT APPLICATION - PATENTANMELDUNG - DEMANDE DE BREVET

AN 918256 EUROPATFULL ED 19990606 EW 199921 FS OS
 TIEN Imaging members containing high performance charge transporting polymers.
 TIDE Bildherstellungselemente die Ladungstransportpolymere hoher Leistung enthalten.
 TIFR Membres de production d' images, comprenant des polymeres de transport de charge a haute performance.
 IN Fuller, Timothy J., 67 Railroad Mills Road, Pittsford, New York 14534-4023, US;
 Teuscher, Leon A., 94 Frankhauser Road, Williamsville New York 14221, US;
 Pai, Damodar M., 72 Shagbark Way, Fairport New York 14450, US;
 Yanus, John F., 924 Little Bardfield Road, Webster New York 14580, US
 PA XEROX CORPORATION, Xerox Square, Rochester, New York 14644, US
 SO Wila-EPZ-1999-H21-T2a
 DS R AT; R BE; R CH; R CY; R DE; R DK; R ES; R FI; R FR; R GB; R GR; R IE; R IT; R LI; R LU; R MC; R NL; R PT; R SE
 PIT EPA2 EUROPÆISCHE PATENTANMELDUNG
 PI EP 918256 A2 19990526
 OD 19990526
 AI EP 1998-121408 19981111
 PRAI US 1997-976238 19971121
 IC ICM G03G005-05
 ICS G03G005-147

L7 ANSWER 3 OF 55 EUROPATFULL COPYRIGHT 2003 WILA

Full
Text

PATENT APPLICATION - PATENTANMELDUNG - DEMANDE DE BREVET

AN 827033 EUROPATFULL ED 19980316 EW 199810 FS OS
 TIEN High performance curable polymers and processes for the preparation

thereof.

TIDE Haertbare Hochleistungspolymeren und Verfahren zu ihrer Herstellung.
 TIFR Polymeres durcissables a haute performance, et procedes de leur preparation.

IN Narang, Ram S., 5 Hunters Drive South, Fairport, NY 14450, US;
 Fuller, Timothy J., 67 Railroad Mills Road, Pittsford, NY 14534-4023, US

PA XEROX CORPORATION, Xerox Square, Rochester New York 14644, US

SO Wila-EPZ-1998-H10-T2a

DS R AT; R BE; R CH; R DE; R DK; R ES; R FI; R FR; R GB; R GR; R IE; R IT;
 R LI; R LU; R MC; R NL; R PT; R SE

PIT EPA2 EUROPÄISCHE PATENTANMELDUNG

PI EP 827033 A2 19980304

OD 19980304

AI EP 1997-306210 19970815

PRAI US 1996-705372 19960829

IC ICM G03F007-038

L7 ANSWER 4 OF 55 EUROPATFULL COPYRIGHT 2003 WILA

Full
Text

PATENT APPLICATION - PATENTANMELDUNG - DEMANDE DE BREVET

AN 827032 EUROPATFULL ED 19980316 EW 199810 FS OS
 TIEN Aqueous developable high performance curable polymers.
 TIDE In Wasser entwickelbare, haertbare Hochleistungspolymeren.
 TIFR Polymeres a haute performance, durcissables et developpables en milieu aqueux.
 IN Narang, Ram S., 390 Hillside Circle, Macedon, NY 14502-9323, US;
 Fuller, Timothy J., 67 Railroad Mills Road, Pittsford, NY 14534-4023, US
 PA XEROX CORPORATION, Xerox Square, Rochester New York 14644, US
 SO Wila-EPZ-1998-H10-T2a
 DS R AT; R BE; R CH; R DE; R DK; R ES; R FI; R FR; R GB; R GR; R IE; R IT;
 R LI; R LU; R MC; R NL; R PT; R SE
 PIT EPA2 EUROPÄISCHE PATENTANMELDUNG
 PI EP 827032 A2 19980304
 OD 19980304
 AI EP 1997-306209 19970815
 PRAI US 1996-697760 19960829
 IC ICM G03F007-038

L7 ANSWER 5 OF 55 EUROPATFULL COPYRIGHT 2003 WILA

Full
Text

PATENT APPLICATION - PATENTANMELDUNG - DEMANDE DE BREVET

AN 827031 EUROPATFULL ED 19980316 EW 199810 FS OS
 TIEN Blends containing curable polymers.
 TIDE Haertbare Polymere enthaltende Mischungen.
 TIFR Melanges contenant des polymeres durcissables.
 IN Narang, Ram S., 5 Hunters Drive South, Fairport, NY 14450, US;
 Fuller, Timothy J., 67 Railroad Mills Road, Pittsford, NY 14534-4023, US
 PA XEROX CORPORATION, Xerox Square, Rochester New York 14644, US
 SO Wila-EPZ-1998-H10-T2a
 DS R AT; R BE; R CH; R DE; R DK; R ES; R FI; R FR; R GB; R GR; R IE; R IT;
 R LI; R LU; R MC; R NL; R PT; R SE
 PIT EPA2 EUROPÄISCHE PATENTANMELDUNG
 PI EP 827031 A2 19980304
 OD 19980304
 AI EP 1997-306208 19970815
 PRAI US 1996-705376 19960829
 IC ICM G03F007-038

L7 ANSWER 6 OF 55 EUROPATFULL COPYRIGHT 2003 WILA

Full
Text

PATENT APPLICATION - PATENTANMELDUNG - DEMANDE DE BREVET

AN 827028 EUROPATFULL ED 19980316 EW 199810 FS OS
 TIEN Hydroxyalkated high performance curable polymers.
 TIDE Hydroxyalkylierte, haertbare Hochleistungs polymere.
 TIFR Polymeres a haute performance, hydroxyalkyles et durcissables.
 IN Narang, Ram S., 5 Hunters Drive South, Fairport NY 14450, US;
 Fuller, Timothy J., 67 Railroad Mills Road, Pittsford NY 14534-4023, US
 PA XEROX CORPORATION, Xerox Square, Rochester New York 14644, US
 SO Wila-EPZ-1998-H10-T2a
 DS R AT; R BE; R CH; R DE; R DK; R ES; R FI; R FR; R GB; R GR; R IE; R IT;
 R LI; R LU; R MC; R NL; R PT; R SE
 PIT EPA2 EUROPÄISCHE PATENTANMELDUNG
 PI EP 827028 A2 19980304
 OD 19980304
 AI EP 1997-306199 19970815
 PRAI US 1996-705365 19960829
 IC ICM G03F007-038

L7 ANSWER 7 OF 55 EUROPATFULL COPYRIGHT 2003 WILA

Full
Text

PATENT APPLICATION - PATENTANMELDUNG - DEMANDE DE BREVET

AN 827027 EUROPATFULL ED 19980316 EW 199810 FS OS
 TIEN Curable compositions.
 TIDE Haertbare Zusammensetzungen.
 TIFR Compositions durcissables.
 IN Narang, Ram S., 5 Hunters Drive South, Fairport, NY 14450, US;
 Fuller, Timothy J., 67 Railroad Mills Road, Pittsford, NY 14534-4023,
 US;
 Smith, Thomas W., 22 Hidden Meadow, Penfield, NY 14526, US;
 Luca, David J., 983 North Winton Road, Rochester, NY 14609, US;
 Mosher, Ralph A., 124 Belmont Street, Rochester, NY 14620, US
 PA XEROX CORPORATION, Xerox Square, Rochester New York 14644, US
 SO Wila-EPZ-1998-H10-T2a
 DS R AT; R BE; R CH; R DE; R DK; R ES; R FI; R FR; R GB; R GR; R IE; R IT;
 R LI; R LU; R MC; R NL; R PT; R SE
 PIT EPA2 EUROPÄISCHE PATENTANMELDUNG
 PI EP 827027 A2 19980304
 OD 19980304
 AI EP 1997-306198 19970815
 PRAI US 1996-705375 19960829
 IC ICM G03F007-038

L7 ANSWER 8 OF 55 EUROPATFULL COPYRIGHT 2003 WILA

Full
Text

PATENT APPLICATION - PATENTANMELDUNG - DEMANDE DE BREVET

AN 827026 EUROPATFULL ED 19980316 EW 199810 FS OS
 TIEN Processes for substituting haloalkylated polymers with unsaturated
 ester, ether, and alkylcarboxymethylene groups.
 TIDE Verfahren zur Substitution von haloalkylierten Polymeren mit
 ungesaettigten Ester-, Ether- und Alkylcarboxymethylengruppen.
 TIFR Procedes de substitution de polymeres haloalkyles avec des groupements
 insatures esters, ethers et alkylcarboxymethylene.
 IN Fuller, Timothy J., 67 Railroad Mills Road, Pittsford, NY 14534-4023,

US;
 Narang, Ram S., 5 Hunters Drive South, Fairport, NY 14450, US;
 Smith, Thomas W., 22 Hidden Meadow, Penfield, NY 14526, US;
 Luca, David J., 983 North Winton Road, Rochester, NY 14609, US;
 Crandall, Raymond K., 88 Butler Drive, Pittsford, NY 14534, US
 PA XEROX CORPORATION, Xerox Square, Rochester New York 14644, US
 SO Wila-EPZ-1998-H10-T2a
 DS R AT; R BE; R CH; R DE; R DK; R ES; R FI; R FR; R GB; R GR; R IE; R IT;
 R LI; R LU; R MC; R NL; R PT; R SE
 PIT EPA2 EUROPÄISCHE PATENTANMELDUNG
PI EP 827026 A2 19980304
OD 19980304
AI EP 1997-306196 19970815
PRAI US 1996-705479 19960829
IC ICM G03F007-038

L7 ANSWER 9 OF 55 EUROPATFULL COPYRIGHT 2003 WILA

Full
Text

PATENT APPLICATION - PATENTANMELDUNG - DEMANDE DE BREVET

AN 826700 EUROPATFULL ED 19980316 EW 199810 FS OS
 TIEN Process for haloalkylation of high performance polymers.
 TIDE Verfahren zur Haloalkylierung von Hochleistungspolymeren.
 TIFR Procede d'haloalkylation de polymeres a haute performance.
 IN Fuller, Timothy J., 67 Railroad Mills Road, Pittsford, NY 14534-4023,
 US;
 Narang, Ram S., 5 Hunters Drive South, Fairport, NY 14450, US;
 Smith, Thomas W., 22 Hidden Meadow, Penfield, NY 14526, US;
 Luca, David J., 983 North Winton Road, Rochester, NY 14609, US;
 Crandall, Raymond K., 88 Butler Drive, Pittsford, NY 14534, US
 PA XEROX CORPORATION, Xerox Square, Rochester New York 14644, US
 SO Wila-EPZ-1998-H10-T1a
 DS R AT; R BE; R CH; R DE; R DK; R ES; R FI; R FR; R GB; R GR; R IE; R IT;
 R LI; R LU; R MC; R NL; R PT; R SE
 PIT EPA2 EUROPÄISCHE PATENTANMELDUNG
PI EP 826700 A2 19980304
OD 19980304
AI EP 1997-306206 19970820
PRAI US 1996-705463 19960829
IC ICM C08F008-24

L7 ANSWER 10 OF 55 EUROPATFULL COPYRIGHT 2003 WILA

Full
Text

PATENT APPLICATION - PATENTANMELDUNG - DEMANDE DE BREVET

AN 413257 EUROPATFULL ED 20000820 EW 199108 FS OS STA B
 TIEN Cyclic poly(aryl ether) oligomers, a process for preparation thereof,
 and polymerization of cyclic poly (aryl ether) oligomers.
 TIDE Zyklische Poly(arylaether)-Oligomere, deren Herstellungsverfahren sowie
 die Polymerisation von zyklischen Poly(arylaether)-Oligomeren.
 TIFR Oligomeres de poly(aryl-ether) cyclique, leur procede de preparation et
 polymerisation d'oligomeres de poly(aryl-ether) cyclique.
 IN Mullins, Michael J., 710 Chatham Drive, Midland, Michigan 48640, US;
 Woo, Edmund P., 300 Mayfield Lane, Midland, Michigan 48640, US
 PA THE DOW CHEMICAL COMPANY, 2030 Dow Center Abbott Road P.O. Box 1967,
 Midland Michigan 48640-1967, US
 SO Wila-EPZ-1991-H08-T1
 DS R AT; R BE; R CH; R DE; R ES; R FR; R GB; R IT; R LI; R NL; R SE
 PIT EPA2 EUROPÄISCHE PATENTANMELDUNG
PI EP 413257 A2 19910220

OD		19910220
AI	EP 1990-115283	19900809
PRAI	US 1989-393503	19890814
	US 1989-402177	19890901
IC	ICM C08G065-40	
	ICS C08L071-10	

L7 ANSWER 11 OF 55 USPATFULL

Full Citing
 Text References

AN 2002:69747 USPATFULL
 TI High performance curable polymers and processes for the preparation thereof
 IN Narang, Ram S., Fairport, NY, United States
 Fuller, Timothy J., Pittsford, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 6365323 B1 20020402
 AI US 1999-268794 19990316 (9)
 RLI Division of Ser. No. US 1996-705372, filed on 29 Aug 1996, now patented,
 Pat. No. US 5945253
 DT Utility
 FS GRANTED
 LN.CNT 3071
 INCL INCLM: 430/280.100
 INCLS: 430/287.100; 430/311.000; 430/325.000; 522/162.000; 522/166.000;
 522/170.000; 522/149.000; 525/536.000; 525/471.000; 525/534.000;
 347/020.000
 NCL NCLM: 430/280.100
 NCLS: 347/020.000; 430/287.100; 430/311.000; 430/325.000; 522/149.000;
 522/162.000; 522/166.000; 522/170.000; 525/471.000; 525/534.000;
 525/536.000
 IC [7]
 ICM: G03F007-038
 ICS: G03F007-26
 EXF 430/280.1; 430/287.1; 430/197; 430/18; 430/311; 430/325; 522/162;
 522/166; 522/170; 522/149
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 12 OF 55 USPATFULL

Full Citing
 Text References

AN 2001:215140 USPATFULL
 TI High performance UV and **heat** crosslinked or chain extended polymers
 IN Smith, Thomas W., Penfield, NY, United States
 Fuller, Timothy J., Pittsford, NY, United States
 Narang, Ram S., Fairport, NY, United States
 Luca, David J., Rochester, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 6323301 B1 20011127
 AI US 2000-635913 20000810 (9)
 RLI Division of Ser. No. US 1998-221690, filed on 23 Dec 1998 Division of
 Ser. No. US 1996-705488, filed on 29 Aug 1996, now patented, Pat. No. US
 6124372
 DT Utility
 FS GRANTED
 LN.CNT 5695
 INCL INCLM: 528/125.000
 INCLS: 528/127.000; 528/128.000; 528/170.000; 528/171.000; 528/172.000;
 528/174.000; 528/196.000; 528/220.000; 528/226.000; 528/228.000;
 528/310.000; 528/373.000; 528/391.000; 528/401.000; 528/405.000;
 528/423.000; 522/162.000; 522/163.000; 522/164.000; 522/165.000;
 522/166.000; 430/280.100; 430/270.100; 430/281.100; 347/020.000
 NCL NCLM: 528/125.000
 NCLS: 347/020.000; 430/270.100; 430/280.100; 430/281.100; 522/162.000;

522/163.000; 522/164.000; 522/165.000; 522/166.000; 528/127.000;
 528/128.000; 528/170.000; 528/171.000; 528/172.000; 528/174.000;
 528/196.000; 528/220.000; 528/226.000; 528/228.000; 528/310.000;
 528/373.000; 528/391.000; 528/401.000; 528/405.000; 528/423.000

IC [7]
 ICM: C08F002-46
 ICS: G03F007-004; B41J002-015; C08G073-22; C08G075-20; C08G065-32
 EXF 528/86; 528/125; 528/127; 528/128; 528/170; 528/171; 528/172; 528/174;
 528/196; 528/373; 528/401; 528/405; 528/423; 528/391; 528/220; 528/226;
 528/228; 528/310; 522/162; 522/163; 522/164; 522/165; 522/166;
 430/270.1; 430/280.1; 430/281.1; 347/20

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 13 OF 55 USPATFULL

Full	Citing
Text	References

AN 2001:169644 USPATFULL
 TI Bonding process
 IN DeLouise, Lisa A., Rochester, NY, United States
 Luca, David J., Rochester, NY, United States
 PA Xerox Corporation (U.S. corporation)
PI US 2001025690 A1 20011004
US 6485130 B2 20021126
AI US 2001-844371 A1 20010427 (9)
RLI Continuation of Ser. No. US 1998-105501, filed on 26 Jun 1998, PENDING
 DT Utility
 FS APPLICATION
 LN.CNT 2715
 INCL INCLM: 156/334.000
 INCLS: 156/272.200
 NCL NCLM: 347/063.000
 NCLS: 347/064.000; 347/065.000; 428/167.000
 IC [7]
 ICM: B32B031-00
 ICS: C09J001-00

L7 ANSWER 14 OF 55 USPATFULL

Full	Citing
Text	References

AN 2001:130708 USPATFULL
 TI Bonding process
 IN DeLouise, Lisa A., Rochester, NY, United States
 Luca, David J., Rochester, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
PI US 6273985 B1 20010814
AI US 1998-105501 19980626 (9)
 DT Utility
 FS GRANTED
 LN.CNT 2572
 INCL INCLM: 156/273.300
 INCLS: 156/273.500; 156/275.500; 156/275.700; 430/286.100; 522/135.000;
 522/172.000
 NCL NCLM: 156/273.300
 NCLS: 156/273.500; 156/275.500; 156/275.700; 430/286.100; 522/135.000;
 522/172.000
 IC [7]
 ICM: B32B031-28
 EXF 156/273.3; 156/273.5; 156/275.1; 156/275.3; 156/275.5; 156/275.7;
 156/330; 156/327; 522/135; 522/172; 430/281.1; 430/286.1; 430/287.1

L7 ANSWER 15 OF 55 USPATFULL

Full	Citing
Text	References

AN 2001:130273 USPATFULL

TI Aqueous developable high performance curable polymers
 IN Narang, Ram S., Fairport, NY, United States
 Fuller, Timothy J., Pittsford, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 6273543 B1 20010814
 AI US 1999-247104 19990209 (9)
 RLI Division of Ser. No. US 1996-697760, filed on 29 Aug 1996, now patented,
 Pat. No. US 6007877
 DT Utility
 FS GRANTED
 LN.CNT 4069
 INCL INCLM: 347/020.000
 INCLS: 347/065.000; 522/162.000; 522/163.000; 522/164.000; 522/165.000;
 522/166.000; 528/125.000; 528/220.000; 528/226.000; 528/228.000;
 528/229.000; 528/391.000; 528/398.000; 528/421.000; 528/423.000;
 528/167.000; 528/168.000; 528/171.000; 528/205.000; 528/211.000
 NCL NCLM: 347/020.000
 NCLS: 347/065.000; 522/162.000; 522/163.000; 522/164.000; 522/165.000;
 522/166.000; 528/125.000; 528/167.000; 528/168.000; 528/171.000;
 528/205.000; 528/211.000; 528/220.000; 528/226.000; 528/228.000;
 528/229.000; 528/391.000; 528/398.000; 528/421.000; 528/423.000
 IC [7]
 ICM: B41J002-01
 ICS: C08G075-02; C08G075-14; C08G075-23; C08G075-30
 EXF 522/162; 522/163; 522/166; 522/164; 522/165; 347/20; 347/65; 528/125;
 528/220; 528/226; 528/228; 528/229; 528/391; 528/398; 528/421; 528/423;
 528/167; 528/168; 528/171; 528/205; 528/211; 430/270.1; 430/280.1;
 430/281.1; 430/286.1
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 16 OF 55 USPATFULL

Full Editing
 Text References

AN 2001:119313 USPATFULL
 TI Method of manufacturing material for forming insulating film
 IN Suzuki, Hidenori, Morigayama-cho, Japan
 Kakinoki, Katsuyuki, Morigayama-cho, Japan
 Nakase, Yoshihisa, Taki Gun, Japan
 Nishikawa, Michinori, Ibaraki, Japan
 Okada, Takashi, Ibaraki, Japan
 Yamada, Kinji, Ibaraki, Japan
 PA JSR Corporation, Tokyo, Japan (non-U.S. corporation)
 PI US 2001009936 A1 20010726
 AI US 2001-760784 A1 20010117 (9)
 PRAI JP 2000-7385 20000117
 JP 2000-175684 20000612
 DT Utility
 FS APPLICATION
 LN.CNT 1446
 INCL INCLM: 524/035.000
 INCLS: 524/435.000; 524/448.000; 524/450.000
 NCL NCLM: 524/035.000
 NCLS: 524/435.000; 524/448.000; 524/450.000
 IC [7]
 ICM: C08J003-00
 ICS: C08K003-34
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 17 OF 55 USPATFULL

Full Editing
 Text References

AN 2001:111229 USPATFULL
 TI Thermal ink jet printhead and process for the preparation thereof
 IN Narang, Ram S., Fairport, NY, United States

Kneezel, Gary A., Webster, NY, United States
 Zhang, Bidan, Beacon, NY, United States
 Fisher, Almon P., Rochester, NY, United States
 Fuller, Timothy J., Pittsford, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 6260956 B1 20010717
 AI US 1998-120746 19980723 (9)
 DT Utility
 FS GRANTED
 LN.CNT 2273
 INCL INCLM: 347/063.000
 INCLS: 347/064.000; 347/065.000; 347/020.000; 347/054.000; 216/027.000;
 156/145.000; 427/504.000
 NCL NCLM: 347/063.000
 NCLS: 156/145.000; 216/027.000; 347/020.000; 347/054.000; 347/064.000;
 347/065.000; 427/504.000
 IC [7]
 ICM: B41J002-04
 ICS: B41J002-015; G01D015-16; G11B005-127
 EXF 347/20; 347/40; 347/47; 347/54; 347/60; 427/504; 216/27; 522/162;
 522/163; 522/164; 522/166; 430/270.1; 430/280.1; 430/281.1; 156/145
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 18 OF 55 USPATFULL

	Full Text	Citing References
AN	2001:111222 USPATFULL	
TI	Photoresist compositions for ink jet printheads	
IN	Smith, Thomas W., Penfield, NY, United States Luca, David J., Rochester, NY, United States McGrane, Kathleen M., Webster, NY, United States	
PA	Xerox Corporation, Stamford, CT, United States (U.S. corporation)	
PI	US 6260949	B1 20010717
AI	US 2000-590927	20000609 (9)
RLI	Division of Ser. No. <u>US 1998-217330</u> , filed on 21 Dec 1998, now patented, Pat. No. <u>US 6139920</u>	
DT	Utility	
FS	GRANTED	
LN.CNT	2856	
INCL	INCLM: 347/044.000 INCLS: 347/020.000; 347/045.000; 430/270.100; 430/280.100; 522/100.000; 522/111.000; 522/142.000; 522/143.000; 522/079.000; 522/146.000; 525/391.000; 525/392.000; 525/396.000; 525/401.000; 525/471.000	
NCL	NCLM: 347/044.000 NCLS: 347/020.000; 347/045.000; 430/270.100; 430/280.100; 522/079.000; 522/100.000; 522/111.000; 522/142.000; 522/143.000; 522/146.000; 525/391.000; 525/392.000; 525/396.000; 525/401.000; 525/471.000	
IC	[7] ICM: B41J002-015 ICS: G03F007-038; C08L063-10; C08L061-16; C08L071-12; C08L079-06; C08L081-06 EXF 522/35; 522/79; 522/100; 522/103; 522/109; 522/110; 522/111; 522/112; 522/142; 522/162; 522/163; 522/164; 522/165; 522/166; 525/391; 525/396; 525/401; 525/404; 525/407; 525/471; 528/87; 427/510; 427/520; 216/27; 347/44; 347/20; 347/45; 264/494; 264/496; 430/270.1; 430/280.1 CAS INDEXING IS AVAILABLE FOR THIS PATENT.	

L7 ANSWER 19 OF 55 USPATFULL

	Full Text	Citing References
AN	2001:39361 USPATFULL	
TI	Hydroxyalkylated high performance curable polymers	
IN	Narang, Ram S., Fairport, NY, United States Fuller, Timothy J., Pittsford, NY, United States	

PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 6203143 B1 20010320
 AI US 1998-159426 19980923 (9)
 RLI Division of Ser. No. US 1996-705365, filed on 29 Aug 1996, now patented,
 Pat. No. US 5849809
 DT Utility
 FS Granted
 LN. CNT 3387
 INCL INCLM: 347/065.000
 INCLS: 427/510.000; 430/270.100; 430/287.100; 522/034.000; 522/039.000;
 522/065.000; 522/139.000; 522/162.000; 522/163.000; 522/164.000;
 522/165.000; 525/453.000; 525/540.000; 525/905.000; 525/906.000;
 525/912.000; 528/125.000; 528/128.000; 528/168.000; 528/170.000;
 528/175.000; 528/220.000; 528/226.000; 528/228.000
 NCL NCLM: 347/065.000
 NCLS: 427/510.000; 430/270.100; 430/287.100; 522/034.000; 522/039.000;
 522/065.000; 522/139.000; 522/162.000; 522/163.000; 522/164.000;
 522/165.000; 525/453.000; 525/540.000; 525/905.000; 525/906.000;
 525/912.000; 528/125.000; 528/128.000; 528/168.000; 528/170.000;
 528/175.000; 528/220.000; 528/226.000; 528/228.000
 IC [7]
 ICM: G03C005-00
 ICS: G03C001-494; B41J002-04; G03F007-038; C08G065-40
 EXF 522/65; 522/39; 522/34; 522/139; 522/162; 522/163; 522/164; 522/165;
 528/220; 528/125; 528/128; 528/175; 528/205; 528/211; 528/226; 528/228;
 528/170; 528/168; 525/905; 525/906; 525/912; 525/453; 525/540;
 430/270.1; 430/287.1; 427/510; 347/20; 347/65
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 20 OF 55 USPATFULL

Full	Citing
Text	References

AN 2001:36564 USPATFULL
 TI Imaging members containing arylene ether alcohol polymers
 IN Fuller, Timothy J., Pittsford, NY, United States
 Yanus, John F., Webster, NY, United States
 Pai, Damodar M., Fairport, NY, United States
 Silvestri, Markus R., Fairport, NY, United States
 Narang, Ram S., Macedon, NY, United States
 Limburg, William W., Penfield, NY, United States
 Renfer, Dale S., Webster, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 6200715 B1 20010313
 AI US 1999-363218 19990729 (9)
 RLI Continuation-in-part of Ser. No. US 1999-326170, filed on 4 Jun 1999
 DT Utility
 FS Granted
 LN. CNT 2245
 INCL INCLM: 430/059.600
 INCLS: 430/096.000
 NCL NCLM: 430/059.600
 NCLS: 430/096.000
 IC [7]
 ICM: G03G005-05
 EXF 430/59.6; 430/96; 430/58.7
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 21 OF 55 USPATFULL

Full	Citing
Text	References

AN 2001:29264 USPATFULL
 TI Crosslinkable binder for charge transport layer of a photoconductor
 IN Fuller, Timothy J., Pittsford, NY, United States
 Silvestri, Markus R., Fairport, NY, United States

Yanus, John F., Webster, NY, United States
 Pai, Damodar M., Fairport, NY, United States
 De Feo, Paul J., Sodus Point, NY, United States
 Renfer, Dale S., Webster, NY, United States
 Ward, Anthony T., Webster, NY, United States
 Limburg, William W., Penfield, NY, United States
 Hammond, Harold F., Webster, NY, United States
 Nolley, Robert W., Stamford, CT, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 6194111 B1 20010227
 AI US 2000-487327 20000119 (9)
 RLI Continuation-in-part of Ser. No. US 1999-326169, filed on 4 Jun 1999,
 now patented, Pat. No. US 6117967
 DT Utility
 FS Granted
 LN.CNT 1308
 INCL INCLM: 430/059.600
 INCLS: 430/096.000
 NCL NCLM: 430/059.600
 NCLS: 430/096.000
 IC [7]
 ICM: G03G005-047
 EXF 430/59.6; 430/58.35; 430/96
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 22 OF 55 USPATFULL

Full Citing
 Text References

AN 2001:18509 USPATFULL
 TI Blends containing photosensitive high performance aromatic ether curable
 polymers
 IN Narang, Ram S., Fairport, NY, United States
 Fuller, Timothy J., Pittsford, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 6184263 B1 20010206
 AI US 1998-220273 19981223 (9)
 RLI Division of Ser. No. US 1996-705376, filed on 29 Aug 1996, now patented,
 Pat. No. US 5958995
 DT Utility
 FS Granted
 LN.CNT 4961
 INCL INCLM: 522/111.000
 INCLS: 522/134.000; 522/135.000; 522/146.000; 522/141.000; 522/162.000;
 522/163.000; 522/164.000; 522/165.000; 522/166.000; 522/142.000;
 522/136.000; 430/270.100; 430/280.100; 525/391.000; 525/420.000;
 525/471.000
 NCL NCLM: 522/111.000
 NCLS: 430/270.100; 430/280.100; 522/134.000; 522/135.000; 522/136.000;
 522/141.000; 522/142.000; 522/146.000; 522/162.000; 522/163.000;
 522/164.000; 522/165.000; 522/166.000; 525/391.000; 525/420.000;
 525/471.000
 IC [7]
 ICM: G03F007-038
 ICS: C08L071-12; C08L081-06
 EXF 522/162; 522/163; 522/164; 522/165; 522/166; 522/111; 522/134; 522/146;
 522/136; 522/135; 522/141; 522/142; 430/270.1; 430/280.1; 525/391;
 525/471; 525/420
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 23 OF 55 USPATFULL

Full Citing
 Text References

AN 2001:10700 USPATFULL
 TI Ink jet printheads containing arylene ether alcohol polymers and

processes for their formation
 IN Fuller, Timothy J., Pittsford, NY, United States
 Yanus, John F., Webster, NY, United States
 Pai, Damodar M., Fairport, NY, United States
 Silvestri, Markus R., Fairport, NY, United States
 Narang, Ram S., Macedon, NY, United States
 Limburg, William W., Penfield, NY, United States
 Renfer, Dale S., Webster, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 6177238 B1 20010123
 AI US 1999-325837 19990604 (9)
 DT Utility
 FS Granted
 LN.CNT 3940
 INCL INCLM: 430/320.000
 INCLS: 347/020.000; 347/065.000
 NCL NCLM: 430/320.000
 NCLS: 347/020.000; 347/065.000
 IC [7]
 ICM: B41J002-16
 ICS: B41J002-01
 EXF 430/320; 347/20; 347/47; 347/65
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 24 OF 55 USPATFULL

Full	Citing
Text	References

AN 2001:7804 USPATFULL
 TI Imaging members containing arylene ether alcohol polymers
 IN Fuller, Timothy J., Pittsford, NY, United States
 Yanus, John F., Webster, NY, United States
 Pai, Damodar M., Fairport, NY, United States
 Silvestri, Markus R., Fairport, NY, United States
 Narang, Ram S., Macedon, NY, United States
 Limburg, William W., Penfield, NY, United States
 Renfer, Dale S., Webster, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 6174636 B1 20010116
 AI US 1999-326170 19990604 (9)
 DT Utility
 FS Granted
 LN.CNT 4007
 INCL INCLM: 430/058.700
 INCLS: 430/056.000; 430/059.600; 430/059.100; 430/096.000
 NCL NCLM: 430/058.700
 NCLS: 430/056.000; 430/059.100; 430/059.600; 430/096.000
 IC [7]
 ICM: G03G005-05
 EXF 430/59.6; 430/59.1; 430/58.7; 430/96; 430/56
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 25 OF 55 USPATFULL

Full	Citing
Text	References

AN 2000:158089 USPATFULL
 TI High performance polymer compositions
 IN Smith, Thomas W., Penfield, NY, United States
 Fuller, Timothy J., Pittsford, NY, United States
 Narang, Ram S., Fairport, NY, United States
 Luca, David J., Rochester, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 6151042 20001121
 AI US 1998-221690 19981223 (9)
 RLI Division of Ser. No. US 1996-705488, filed on 29 Aug 1996

DT Utility
 FS Granted
 LN.CNT 5603
 INCL INCLM: 347/020.000
 INCLS: 347/063.000; 347/064.000; 347/065.000; 522/034.000; 522/035.000;
 522/036.000; 522/162.000; 522/163.000; 522/164.000; 522/165.000;
 522/166.000; 430/270.100; 430/286.100; 430/287.100
 NCL NCLM: 347/020.000
 NCLS: 347/063.000; 347/064.000; 347/065.000; 430/270.100; 430/286.100;
 430/287.100; 522/034.000; 522/035.000; 522/036.000; 522/162.000;
 522/163.000; 522/164.000; 522/165.000; 522/166.000
 IC [7]
 ICM: B41J002-178
 ICS: B41J002-235; G03F007-038; C08F002-46
 EXF 347/20; 347/63; 347/64; 347/65; 522/34; 522/35; 522/36; 522/162;
 522/163; 522/164; 522/165; 522/166; 430/270.1; 430/286.1; 430/287.1
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 26 OF 55 USPATFULL

Full
 Text Citing
 References

AN 2000:145966 USPATFULL
 TI Photoresist compositions
 IN Smith, Thomas W., Penfield, NY, United States
 Luca, David J., Rochester, NY, United States
 McGrane, Kathleen M., Webster, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 6139920 20001031
 AI US 1998-217330 19981221 (9)
 DT Utility
 FS Granted
 LN.CNT 3278
 INCL INCLM: 427/510.000
 INCLS: 427/520.000; 522/079.000; 522/035.000; 522/111.000; 522/146.000;
 525/391.000; 525/396.000; 525/401.000; 525/404.000; 525/407.000;
 525/471.000; 430/270.100; 430/280.100
 NCL NCLM: 427/510.000
 NCLS: 427/520.000; 430/270.100; 430/280.100; 522/035.000; 522/079.000;
 522/111.000; 522/146.000; 525/391.000; 525/396.000; 525/401.000;
 525/404.000; 525/407.000; 525/471.000
 IC [7]
 ICM: G03F007-038
 ICS: C08L063-10; C08L063-04; C08L071-12
 EXF 522/100; 522/103; 522/109; 522/110; 522/111; 522/112; 522/162; 522/163;
 522/164; 522/165; 522/166; 522/79; 522/35; 522/146; 528/87; 525/391;
 525/396; 525/401; 525/404; 525/407; 525/471; 427/510; 427/520
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 27 OF 55 USPATFULL

Full
 Text Citing
 References

AN 2000:128404 USPATFULL
 TI High performance polymer compositions having photosensitivity-imparting
 substituents and thermal sensitivity-imparting substituents
 IN Smith, Thomas W., Penfield, NY, United States
 Fuller, Timothy J., Pittsford, NY, United States
 Narang, Ram S., Fairport, NY, United States
 Luca, David J., Rochester, NY, United States
 PA Xerox Corporation, Stamford, CA, United States (U.S. corporation)
 PI US 6124372 20000926
 AI US 1996-705488 19960829 (8)
 DT Utility
 FS Granted
 LN.CNT 5807

INCL INCLM: 522/035.000
 INCLS: 522/077.000; 522/080.000; 522/149.000; 522/162.000; 522/163.000;
 522/165.000; 522/166.000; 522/904.000; 522/905.000; 106/020.000D;
 430/270.100; 430/280.100; 430/281.100; 347/020.000
 NCL NCLM: 522/035.000
 NCLS: 347/020.000; 430/270.100; 430/280.100; 430/281.100; 522/077.000;
 522/080.000; 522/149.000; 522/162.000; 522/163.000; 522/165.000;
 522/166.000; 522/904.000; 522/905.000
 IC [7]
 ICM: C08F002-50
 ICS: G03F007-004; B41J002-015
 EXF 522/35; 522/904; 522/905; 522/162; 522/163; 522/178; 522/149; 522/79;
 522/80; 522/165; 522/166; 430/270.1; 430/280.1; 430/281.1
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 28 OF 55 USPATFULL

Full	Citing
Text	References

AN 2000:121610 USPATFULL
 TI Arylene ether alcohol polymers
 IN Fuller, Timothy J., Pittsford, NY, United States
 Yanus, John F., Webster, NY, United States
 Pai, Damodar M., Fairport, NY, United States
 Silvestri, Markus R., Fairport, NY, United States
 Narang, Ram S., Macedon, NY, United States
 Limburg, William W., Penfield, NY, United States
 Renfer, Dale S., Webster, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 6117967 20000912
 AI US 1999-326169 19990604 (9)
 DT Utility
 FS Granted
 LN.CNT 3056
 INCL INCLM: 528/125.000
 INCLS: 528/127.000; 528/128.000; 528/488.000; 528/499.000; 522/111.000;
 522/146.000; 522/149.000; 522/155.000; 522/162.000; 430/270.100;
 430/280.100; 430/281.100; 430/311.000
 NCL NCLM: 528/125.000
 NCLS: 430/270.100; 430/280.100; 430/281.100; 430/311.000; 522/111.000;
 522/146.000; 522/149.000; 522/155.000; 522/162.000; 528/127.000;
 528/128.000; 528/488.000; 528/499.000
 IC [7]
 ICM: C08G014-00
 ICS: C08G008-02
 EXF 528/125; 528/127; 528/128; 528/488; 528/499; 522/111; 522/146; 522/149;
 522/155; 522/162; 430/270.1; 430/280.1; 430/281.1; 430/311
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 29 OF 55 USPATFULL

Full	Citing
Text	References

AN 2000:91608 USPATFULL
 TI Halomethylated high performance curable polymers
 IN Narang, Ram S., Fairport, NY, United States
 Fuller, Timothy J., Pittsford, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 6090453 20000718
 AI US 1998-163672 19980930 (9)
 RLI Division of Ser. No. US 1996-705490, filed on 29 Aug 1996, now patented,
 Pat. No. US 5863963
 DT Utility
 FS Granted
 LN.CNT 2631
 INCL INCLM: 427/504.000

INCLS: 427/510.000; 430/270.100; 430/286.100; 522/162.000; 522/163.000;
 522/164.000; 522/165.000; 522/166.000; 156/275.300; 156/275.500;
 528/125.000; 528/127.000; 528/128.000; 528/171.000; 528/174.000;
 528/373.000; 528/401.000; 528/405.000

NCL NCLM: 427/504.000
 NCLS: 156/275.300; 156/275.500; 427/510.000; 430/270.100; 430/286.100;
 522/162.000; 522/163.000; 522/164.000; 522/165.000; 522/166.000;
 528/125.000; 528/127.000; 528/128.000; 528/171.000; 528/174.000;
 528/373.000; 528/401.000; 528/405.000

IC [7]
 ICM: C08F002-46
 ICS: G03F007-038; C08G008-02; C08G014-00

EXF 522/162; 522/163; 522/164; 522/165; 522/166; 430/270.1; 430/286.1;
 156/272.2; 156/275.1; 156/275.3; 156/275.5; 427/504; 427/510; 528/125;
 528/126; 528/127; 528/128; 528/171; 528/172; 528/174; 528/373; 528/401;
 528/405; 347/20

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 30 OF 55 USPATFULL

Full Citing
 Text References

AN 2000:88242 USPATFULL
 TI Process for direct substitution of high performance polymers with unsaturated ester groups
 IN Fuller, Timothy J., Pittsford, NY, United States
 Narang, Ram S., Fairport, NY, United States
 Smith, Thomas W., Penfield, NY, United States
 Luca, David J., Rochester, NY, United States
 Crandall, Raymond K., Pittsford, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 6087414 20000711
 AI US 1998-221278 19981223 (9)
 RLI Division of Ser. No. US 1996-697761, filed on 29 Aug 1996, now patented,
 Pat. No. US 5889077
 DT Utility
 FS Granted
 LN.CNT 2580
 INCL INCLM: 522/162.000
 INCLS: 522/163.000; 522/164.000; 522/165.000; 522/166.000; 522/905.000;
 528/125.000; 528/128.000; 528/127.000; 528/129.000; 528/143.000;
 528/170.000; 528/171.000; 528/179.000; 528/205.000; 528/220.000;
 528/227.000; 528/230.000; 528/246.000; 528/306.000; 528/391.000;
 528/423.000; 528/226.000; 528/228.000; 430/270.100; 430/280.100;
 430/286.100
 NCL NCLM: 522/162.000
 NCLS: 430/270.100; 430/280.100; 430/286.100; 522/163.000; 522/164.000;
 522/165.000; 522/166.000; 522/905.000; 528/125.000; 528/127.000;
 528/128.000; 528/129.000; 528/143.000; 528/170.000; 528/171.000;
 528/179.000; 528/205.000; 528/220.000; 528/226.000; 528/227.000;
 528/228.000; 528/230.000; 528/246.000; 528/306.000; 528/391.000;
 528/423.000
 IC [7]
 ICM: C08J003-28
 ICS: G03F007-038; C08G085-00; C08G065-38; C08G073-06
 EXF 522/163; 522/162; 522/164; 522/165; 522/166; 522/905; 430/18; 430/270.1;
 430/280.1; 430/286.1; 430/287.1; 430/311; 430/320; 528/220; 528/125;
 528/128; 528/127; 528/129; 528/143; 528/170; 528/171; 528/179; 528/205;
 528/227; 528/232; 528/246; 528/306
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 31 OF 55 USPATFULL

Full Citing
 Text References

AN 2000:14872 USPATFULL

TI Curable compositions
 IN Narang, Ram S., Fairport, NY, United States
 Fuller, Timothy J., Pittsford, NY, United States
 Smith, Thomas W., Penfield, NY, United States
 Luca, David J., Rochester, NY, United States
 Mosher, Ralph A., Rochester, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 6022095 20000208
 AI US 1998-221024 19981223 (9)
 RLI Division of Ser. No. US 1996-705375, filed on 29 Aug 1996
 DT Utility
 FS Granted
 LN.CNT 5214
 INCL INCLM: 347/020.000
 INCLS: 347/054.000; 528/125.000; 528/220.000; 528/367.000; 528/370.000;
 528/391.000; 528/422.000; 522/162.000; 522/163.000; 522/164.000;
 522/165.000; 522/166.000; 430/280.100; 430/270.100; 430/186.100;
 156/273.300
 NCL NCLM: 347/020.000
 NCLS: 156/273.300; 347/054.000; 430/270.100; 430/280.100; 522/162.000;
 522/163.000; 522/164.000; 522/165.000; 522/166.000; 528/125.000;
 528/220.000; 528/367.000; 528/370.000; 528/391.000; 528/422.000
 IC [6]
 ICM: B41J002-015
 ICS: B41J002-04; G01D015-18; G03C001-72
 EXF 347/20; 347/47; 347/44; 347/54; 522/162; 522/163; 522/164; 522/165;
 522/166; 525/912; 525/913; 525/905; 525/906; 525/907; 525/931; 528/220;
 528/391; 528/125; 528/211; 528/422; 528/367; 528/370; 156/273.3;
 430/270.1; 430/280.1; 430/286.1
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 32 OF 55 USPATFULL

Full Listing
 Text References

AN 1999:170270 USPATFULL
 TI Aqueous developable high performance photosensitive curable aromatic
 ether polymers
 IN Narang, Ram S., Fairport, NY, United States
 Fuller, Timothy J., Pittsford, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 6007877 19991228
 AI US 1996-697760 19960829 (8)
 DT Utility
 FS Granted
 LN.CNT 3899
 INCL INCLM: 427/510.000
 INCLS: 347/020.000; 347/047.000; 522/079.000; 522/080.000; 522/162.000;
 522/163.000; 522/164.000; 522/165.000; 522/166.000; 525/471.000;
 525/534.000; 525/540.000; 525/905.000; 525/906.000; 525/907.000;
 525/912.000; 528/220.000; 528/310.000; 528/372.000; 528/125.000;
 528/126.000; 528/127.000; 528/171.000; 528/174.000; 430/270.100;
 430/280.100; 430/281.100
 NCL NCLM: 427/510.000
 NCLS: 347/020.000; 347/047.000; 430/270.100; 430/280.100; 430/281.100;
 522/079.000; 522/080.000; 522/162.000; 522/163.000; 522/164.000;
 522/165.000; 522/166.000; 525/471.000; 525/534.000; 525/540.000;
 525/905.000; 525/906.000; 525/907.000; 525/912.000; 528/125.000;
 528/126.000; 528/127.000; 528/171.000; 528/174.000; 528/220.000;
 528/310.000; 528/372.000
 IC [6]
 ICM: C08F002-50
 ICS: G03F007-004; C08G008-02; C08G065-38
 EXF 522/35; 522/904; 522/905; 522/149; 522/162; 522/163; 522/178; 522/164;
 522/166; 430/270.1; 430/280.1; 430/281.1

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 33 OF 55 USPATFULL

[Full Text](#) [Citing References](#)

AN 1999:155808 USPATFULL
 TI Curable compositions containing photosensitive high performance aromatic ether polymers
 IN Narang, Ram S., Fairport, NY, United States
 Fuller, Timothy J., Pittsford, NY, United States
 Smith, Thomas W., Penfield, NY, United States
 Luca, David J., Rochester, NY, United States
 Mosher, Ralph A., Rochester, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 5994425 19991130
 AI US 1996-705375 19960829 (8)
 DT Utility
 FS Granted
 LN.CNT 5306
 INCL INCLM: 522/035.000
 INCLS: 522/146.000; 522/149.000; 522/162.000; 522/163.000; 522/165.000;
 522/166.000; 522/178.000; 522/904.000; 522/905.000; 106/020.000D;
 347/020.000; 430/270.100; 430/280.100; 430/281.100
 NCL NCLM: 522/035.000
 NCLS: 106/031.780; 347/020.000; 430/270.100; 430/280.100; 430/281.100;
 522/146.000; 522/149.000; 522/162.000; 522/163.000; 522/165.000;
 522/166.000; 522/178.000; 522/904.000; 522/905.000
 IC [6]
 ICM: C08F002-46
 ICS: G03F007-004; C08L063-00; C08L071-12
 EXF 522/35; 522/904; 522/905; 522/162; 522/163; 522/178; 522/146; 522/149;
 522/165; 522/166; 430/270.1; 430/280.1; 430/281.1
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 34 OF 55 USPATFULL

[Full Text](#) [Citing References](#)

AN 1999:136568 USPATFULL
 TI Conducting compositions
 IN Fuller, Timothy J., Pittsford, NY, United States
 Pai, Damodar M., Fairport, NY, United States
 Yanus, John F., Webster, NY, United States
 DeFeo, Paul J., Sodus Point, NY, United States
 Silvestri, Markus R., Fairport, NY, United States
 Narang, Ram S., Macedon, NY, United States
 Limburg, William W., Penfield, NY, United States
 Renfer, Dale S., Webster, NY, United States
 Stolka, Milan, Fairport, NY, United States
 Abkowitz, Martin A., Webster, NY, United States
 Mosher, Ralph A., Rochester, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 5976418 19991102
 AI US 1998-186542 19981105 (9)
 DT Utility
 FS Granted
 LN.CNT 1826
 INCL INCLM: 252/500.000
 INCLS: 252/510.000; 252/511.000; 427/385.500; 427/058.000; 427/393.100
 NCL NCLM: 252/500.000
 NCLS: 252/510.000; 252/511.000; 427/058.000; 427/385.500; 427/393.100
 IC [6]
 ICM: H01B001-00
 ICS: H01B001-12; H01B001-20; B05D005-12
 EXF 252/510; 252/511; 252/500; 430/56; 430/59; 430/66; 430/96; 528/125;

528/126; 528/176; 528/185; 528/190; 528/397; 528/503; 525/390; 525/437;
 524/765; 524/779; 427/385.5; 427/58; 427/393.1

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 35 OF 55 USPATFULL

Full Citing
 Text References

AN 1999:117566 USPATFULL
 TI Blends containing photosensitive high performance aromatic ether curable polymers
 IN Narang, Ram S., Fairport, NY, United States
 Fuller, Timothy J., Pittsford, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 5958995 19990928
 AI US 1996-705376 19960829 (8)
 DT Utility
 FS Granted
 LN.CNT 4535
 INCL INCLM: 522/035.000
 INCLS: 522/111.000; 522/142.000; 522/146.000; 522/162.000; 522/163.000;
 522/178.000; 522/904.000; 522/905.000; 522/165.000; 522/166.000;
 430/270.100; 430/280.100; 430/281.100; 347/220.000; 106/020.000D
 NCL NCLM: 522/035.000
 NCLS: 347/220.000; 430/270.100; 430/280.100; 430/281.100; 522/111.000;
 522/142.000; 522/146.000; 522/162.000; 522/163.000; 522/165.000;
 522/166.000; 522/178.000; 522/904.000; 522/905.000
 IC [6]
 ICM: C08F002-46
 ICS: G03F007-004; C08L071-12
 EXF 522/162; 522/163; 522/178; 522/111; 522/142; 522/146; 522/35; 522/904;
 522/905; 522/165; 522/166; 430/270.1; 430/281.1; 430/280.1
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 36 OF 55 USPATFULL

Full Citing
 Text References

AN 1999:102642 USPATFULL
 TI High performance curable polymers and processes for the preparation thereof
 IN Narang, Ram S., Fairport, NY, United States
 Fuller, Timothy J., Pittsford, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 5945253 19990831
 AI US 1996-705376 19960829 (8)
 DT Utility
 FS Granted
 LN.CNT 3038
 INCL INCLM: 430/280.100
 INCLS: 430/287.100; 430/311.000; 430/325.000; 522/162.000; 522/166.000;
 522/170.000; 522/149.000; 525/536.000; 525/471.000; 525/534.000
 NCL NCLM: 430/280.100
 NCLS: 430/287.100; 430/311.000; 430/325.000; 522/149.000; 522/162.000;
 522/166.000; 522/170.000; 525/471.000; 525/534.000; 525/536.000
 IC [6]
 ICM: G03F007-038
 ICS: G03F007-26
 EXF 430/280.1; 430/287.1; 430/311; 430/325; 522/162; 522/166; 522/170;
 522/149; 525/471; 525/534; 525/536
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 37 OF 55 USPATFULL

Full Citing
 Text References

AN 1999:96157 USPATFULL

TI Stabilized porous, electrically conductive substrates
 IN Kneezel, Gary A., Webster, NY, United States
 Narang, Ram S., Fallport, NY, United States
 Fuller, Timothy J., Pittsford, NY, United States
 John, Peter J., Rochester, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 5939206 19990817
 AI US 1996-705916 19960829 (8)
 DT Utility
 FS Granted
 LN.CNT 2233
 INCL INCLM: 428/480.000
 INCLS: 428/209.000; 428/901.000; 174/256.000; 174/258.000; 174/260.000;
 257/713.000
 NCL NCLM: 428/480.000
 NCLS: 174/256.000; 174/258.000; 174/260.000; 257/713.000; 428/209.000;
 428/901.000
 IC [6]
 ICM: B32B027-06
 EXF 257/701; 257/702; 257/713; 428/209; 428/480; 428/901; 174/256; 174/258;
 174/260
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 38 OF 55 USPATFULL

Full	Citing
Text	References

AN 1999:40494 USPATFULL
 TI Process for direct substitution of high performance polymers with
 unsaturated ester groups
 IN Fuller, Timothy J., Pittsford, NY, United States
 Narang, Ram S., Fairport, NY, United States
 Smith, Thomas W., Penfield, NY, United States
 Luca, David J., Rochester, NY, United States
 Crandall, Raymond K., Pittsford, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 5889077 19990330
 AI US 1996-697761 19960829 (8)
 DT Utility
 FS Granted
 LN.CNT 2674
 INCL INCLM: 522/162.000
 INCLS: 522/163.000; 522/178.000; 522/111.000; 522/142.000; 522/146.000;
 522/905.000; 522/035.000; 522/904.000
 NCL NCLM: 522/162.000
 NCLS: 522/035.000; 522/111.000; 522/142.000; 522/146.000; 522/163.000;
 522/178.000; 522/904.000; 522/905.000
 IC [6]
 ICM: C08J003-28
 EXF 522/162; 522/163; 522/178; 522/111; 522/142; 522/146; 522/35; 522/904;
 522/905
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 39 OF 55 USPATFULL

Full	Citing
Text	References

AN 1999:33726 USPATFULL
 TI Imaging members containing high performance charge transporting polymers
 IN Fuller, Timothy J., Pittsford, NY, United States
 Teuscher, Leon A., Williamsville, NY, United States
 Pai, Damodar M., Fairport, NY, United States
 Yanus, John F., Webster, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 5882814 19990316
 AI US 1997-976238 19971121 (8)

DT Utility
 FS Granted
 LN.CNT 1957
 INCL INCLM: 430/059.000
 INCLS: 430/096.000
 NCL NCLM: 430/058.350
 NCLS: 430/096.000
 IC [6]
 ICM: G03G005-047
 EXF 430/58; 430/59; 430/96
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 40 OF 55 USPATFULL

Full Citing
 Text References

AN 1999:12971 USPATFULL
 TI Halomethylated high performance curable polymers
 IN Narang, Ram S., Fairport, NY, United States
 Fuller, Timothy J., Pittsford, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 5863963 19990126
 AI US 1996-705490 19960829 (8)
 DT Utility
 FS Granted
 LN.CNT 2573
 INCL INCLM: 522/162.000
 INCLS: 522/164.000; 522/166.000; 522/079.000; 522/080.000; 525/125.000;
 525/128.000; 525/176.000; 525/185.000; 525/190.000; 525/191.000;
 525/193.000; 525/397.000; 525/401.000; 347/020.000; 430/270.100;
 430/287.100
 NCL NCLM: 522/162.000
 NCLS: 347/020.000; 430/270.100; 430/287.100; 522/079.000; 522/080.000;
 522/164.000; 522/166.000; 525/125.000; 525/128.000; 525/176.000;
 525/185.000; 525/190.000; 525/191.000; 525/193.000; 525/397.000;
 525/401.000
 IC [6]
 ICM: C08F002-46
 ICS: C08F283-00; C08G014-00
 EXF 522/35; 522/904; 522/905; 522/162; 522/163; 522/178; 522/149; 522/79;
 522/80; 522/165; 522/166; 522/164; 525/125; 525/128; 525/176; 525/185;
 525/190; 525/191; 525/193; 525/397; 525/401; 347/20; 430/270.1;
 430/287.1
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 41 OF 55 USPATFULL

Full Citing
 Text References

AN 1998:157410 USPATFULL
 TI Hydroxyalkylated high performance curable polymers
 IN Narang, Ram S., Fairport, NY, United States
 Fuller, Timothy J., Pittsford, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 5849809 19981215
 AI US 1996-705365 19960829 (8)
 DT Utility
 FS Granted
 LN.CNT 3228
 INCL INCLM: 522/035.000
 INCLS: 522/149.000; 522/162.000; 522/163.000; 522/165.000; 522/166.000;
 522/904.000; 522/905.000; 522/178.000; 430/280.100; 430/270.100;
 430/287.100; 430/286.100; 347/020.000; 427/510.000; 427/517.000;
 427/520.000
 NCL NCLM: 522/035.000
 NCLS: 347/020.000; 427/510.000; 427/517.000; 427/520.000; 430/270.100;

430/280.100; 430/286.100; 430/287.100; 522/149.000; 522/162.000;
 522/163.000; 522/165.000; 522/166.000; 522/178.000; 522/904.000;
 522/905.000

IC [6]
 ICM: C08L081-06
 ICS: C08L075-16; C08L071-12
 EXF 522/35; 522/904; 522/905; 522/149; 522/162; 522/163; 522/178; 522/165;
 522/166; 347/20; 430/270.1; 430/280.1; 430/286.1; 430/287.1; 427/510;
 427/517; 427/520

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 42 OF 55 USPATFULL

Full Citing
 Text References

AN 1998:144181 USPATFULL
 TI Sulfo-pendent aryletherketone polymer film containing NLO chromophore
 IN Arnold, Fred E., Centerville, OH, United States
 Venkatasubramanian, Narayanan, Bellbrook, OH, United States
 PA The United States of America as represented by the Secretary of the Air
 Force, Washington, DC, United States (U.S. government)
 PI US 5837783 19981117
 AI US 1997-848444 19970508 (8)
 DT Utility
 FS Granted
 LN.CNT 252
 INCL INCLM: 525/471.000
 INCLS: 528/125.000; 528/128.000
 NCL NCLM: 525/471.000
 NCLS: 528/125.000; 528/128.000
 IC [6]
 ICM: C08G008-02
 EXF 528/125; 528/128; 528/471
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 43 OF 55 USPATFULL

Full Citing
 Text References

AN 1998:63620 USPATFULL
 TI Process for substituting haloalkylated polymers with unsaturated ester,
 ether, and alkylcarboxymethylene groups
 IN Fuller, Timothy J., Pittsford, NY, United States
 Narang, Ram S., Fairport, NY, United States
 Smith, Thomas W., Penfield, NY, United States
 Luca, David J., Rochester, NY, United States
 Crandall, Raymond K., Pittsford, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 5761809 19980609
 AI US 1996-705479 19960829 (8)
 DT Utility
 FS Granted
 LN.CNT 3762
 INCL INCLM: 029/890.100
 INCLS: 528/176.000; 528/183.000; 528/185.000; 528/190.000; 528/191.000;
 528/196.000; 528/202.000; 528/373.000; 528/391.000; 528/401.000;
 528/423.000; 522/071.000; 522/165.000; 428/423.100; 428/482.000;
 029/890.100; 430/627.000
 NCL NCLM: 029/890.100
 NCLS: 347/020.000; 427/510.000; 428/423.100; 428/482.000; 430/286.100;
 430/287.100; 430/627.000; 522/071.000; 522/079.000; 522/080.000;
 522/149.000; 522/162.000; 522/163.000; 522/165.000; 522/166.000;
 528/176.000; 528/183.000; 528/185.000; 528/190.000; 528/191.000;
 528/196.000; 528/202.000; 528/373.000; 528/391.000; 528/401.000;
 528/423.000
 IC [6]

ICM: H01R043-00
 ICS: C08G063-00; C03C001-005
 EXF 528/176; 528/183; 528/190; 528/185; 528/191; 528/196; 528/202; 528/373;
 528/391; 528/401; 528/423; 522/71; 522/165; 428/423.1; 428/482;
 029/890.1; 430/627
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 44 OF 55 USPATFULL

Full	Citing
Text	References

AN 1998:55022 USPATFULL
 TI Process for haloalkylation of high performance polymers
 IN Fuller, Timothy J., Pittsford, NY, United States
 Narang, Ram S., Fairport, NY, United States
 Smith, Thomas W., Penfield, NY, United States
 Luca, David J., Rochester, NY, United States
 Crandall, Raymond K., Pittsford, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 5753783 19980519
 AI US 1997-920240 19970828 (8)
 RLI Division of Ser. No. US 1996-705463, filed on 29 Aug 1996, now patented,
 Pat. No. US 5739254
 DT Utility
 FS Granted
 LN.CNT 3482
 INCL INCLM: 525/471.000
 INCLS: 528/125.000; 528/126.000; 528/127.000; 528/128.000; 528/171.000;
 528/172.000; 528/174.000; 528/373.000; 528/401.000; 528/405.000;
 525/471.000; 525/534.000; 525/535.000; 525/540.000; 524/081.000;
 524/167.000; 524/284.000; 524/745.000; 522/005.000; 522/071.000;
 522/162.000; 522/167.000; 430/311.000
 NCL NCLM: 525/471.000
 NCLS: 347/020.000; 430/286.100; 430/287.100; 430/311.000; 522/005.000;
 522/071.000; 522/162.000; 522/163.000; 522/165.000; 522/166.000;
 522/167.000; 524/081.000; 524/167.000; 524/284.000; 524/745.000;
 525/534.000; 525/535.000; 525/540.000; 528/125.000; 528/126.000;
 528/127.000; 528/128.000; 528/171.000; 528/172.000; 528/174.000;
 528/373.000; 528/401.000; 528/405.000
 IC [6]
 ICM: C08F283-00
 ICS: C08G014-00
 EXF 528/125; 528/126; 528/127; 528/128; 528/171; 528/172; 528/174; 528/373;
 528/401; 528/405; 525/471; 525/534; 525/535; 525/540; 524/81; 524/167;
 524/284; 524/745; 522/5; 522/71; 522/162; 522/167; 430/311
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 45 OF 55 USPATFULL

Full	Citing
Text	References

AN 1998:39644 USPATFULL
 TI Process for haloalkylation of high performance polymers
 IN Fuller, Timothy J., Pittsford, NY, United States
 Narang, Ram S., Fairport, NY, United States
 Smith, Thomas W., Penfield, NY, United States
 Luca, David J., Rochester, NY, United States
 Grandall, Raymond K., Pittsford, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
 PI US 5739254 19980414
 AI US 1996-705463 19960829 (8)
 DT Utility
 FS Granted
 LN.CNT 3433
 INCL INCLM: 528/125.000
 INCLS: 528/125.000; 528/126.000; 528/176.000; 528/185.000; 528/190.000;

528/191.000; 528/193.000; 528/397.000; 528/401.000; 528/503.000;
 525/390.000; 525/437.000; 525/534.000; 525/536.000; 525/765.000;
 525/779.000; 525/783.000
 NCL NCLM: 528/125.000
 NCLS: 347/065.000; 524/765.000; 524/779.000; 524/783.000; 525/390.000;
 525/437.000; 525/534.000; 525/536.000; 528/126.000; 528/176.000;
 528/185.000; 528/190.000; 528/191.000; 528/193.000; 528/397.000;
 528/401.000; 528/503.000
 IC [6]
 ICM: C08G008-02
 ICS: C08G014-00
 EXF 528/125; 528/126; 528/128; 528/176; 528/185; 528/190; 528/191; 528/397;
 528/193; 528/401; 528/503; 525/390; 525/437; 525/534; 525/536; 524/765;
 524/779; 524/783
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 46 OF 55 USPATFULL

	Full Text	Citing References
AN	94:18144 USPATFULL	
TI	Poly(arylene ether ketone), process for producing same and its use	
IN	Matsumura, Shunichi, Iwakuni, Japan Itoh, Seiji, Iwakuni, Japan Inata, Hiroo, Iwakuni, Japan Sadanobu, Jiro, Iwakuni, Japan	
PA	Teijin Limited, Osaka, Japan (non-U.S. corporation)	
PI	US 5290906	19940301
AI	US 1991-644978	19910123 (7)
PRAI	JP 1989-127742	19890523
	JP 1989-331138	19891222
	JP 1989-331139	19891222
DT	Utility	
FS	Granted	
LN.CNT	1114	
INCL	INCLM: 528/125.000 INCLS: 528/126.000; 528/174.000; 528/175.000; 528/220.000; 525/390.000; 525/534.000; 428/357.000; 428/364.000; 428/394.000; 428/411.100	
NCL	NCLM: 528/125.000 NCLS: 428/357.000; 428/364.000; 428/394.000; 428/411.100; 525/390.000; 525/534.000; 528/126.000; 528/174.000; 528/175.000; 528/220.000	
IC	[5] ICM: C08G008-02 ICS: C08G014-00; C08G061-12; B32B009-00	
EXF	528/125; 528/126; 528/220; 528/174; 528/175; 525/534; 525/390; 428/411.1; 428/394; 428/357; 428/364	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.		

L7 ANSWER 47 OF 55 USPATFULL

	Full Text	Citing References
AN	93:105078 USPATFULL	
TI	Polyarylene ethers	
IN	Pfaendner, Rudolf, Rimbach/Odenwald, Germany, Federal Republic of Kainmuller, Thomas, Lindenfels/Odenwald, Germany, Federal Republic of Hoffmann, Kurt, Lautertal, Germany, Federal Republic of Kramer, Andreas, Duedingen, Switzerland Stockinger, Friedrich, Courtepin, Switzerland	
PA	Ciba-Geigy Corporation, Ardsley, NY, United States (U.S. corporation)	
PI	US 5270435	19931214
AI	US 1992-816839	19920109 (7)
RLI	Continuation of Ser. No. <u>US 1990-537197</u> , filed on 12 Jun 1990, now abandoned	
PRAI	CH 1989-2343	19890623
	CH 1990-964	19900323

DT Utility
 FS Granted
 LN.CNT 443
 INCL INCLM: 528/171.000
 INCLS: 528/125.000; 528/174.000; 528/219.000
 NCL NCLM: 528/171.000
 NCLS: 528/125.000; 528/174.000; 528/219.000
 IC [5]
 ICM: C08G075-00
 ICS: C08G065-38
 EXF 528/125; 528/171; 528/174; 528/219; 428/411.1; 524/611
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 48 OF 55 USPATFULL

Full Citing
 Text References

AN 93:98482 USPATFULL
 TI Cyclic poly(aryl ether) oligomers
 IN Mullins, Michael J., Midland, MI, United States
 Woo, Edmund P., Midland, MI, United States
 Balon, Kimberly E., Midland, MI, United States
 Murray, Daniel J., Midland, MI, United States
 Chen, Cheng-Cheng C., Midland, MI, United States
 PA The Dow Chemical Company, Midland, MI, United States (U.S. corporation)
 PI US 5264538 19931123
 AI US 1990-544718 19900627 (7)
 RLI Continuation-in-part of Ser. No. US 1989-393503, filed on 14 Aug 1989,
 now abandoned
 DT Utility
 FS Granted
 LN.CNT 772
 INCL INCLM: 528/226.000
 INCLS: 528/125.000; 528/126.000; 528/128.000; 528/167.000; 528/170.000;
 528/171.000; 528/174.000; 528/175.000; 528/206.000; 528/220.000;
 548/417.000; 548/418.000; 548/419.000; 548/423.000; 549/011.000;
 549/012.000; 549/349.000; 549/354.000
 NCL NCLM: 528/226.000
 NCLS: 528/125.000; 528/126.000; 528/128.000; 528/167.000; 528/170.000;
 528/171.000; 528/174.000; 528/175.000; 528/206.000; 528/220.000;
 548/417.000; 548/418.000; 548/419.000; 548/423.000; 549/011.000;
 549/012.000; 549/349.000; 549/354.000
 IC [5]
 ICM: C08G002-00
 ICS: C08G075-00
 EXF 528/125; 528/126; 528/128; 528/167; 528/170; 528/171; 528/174; 528/175;
 528/206; 528/220; 528/226; 549/11; 549/12; 549/349; 549/354; 548/423;
 548/417-419
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 49 OF 55 USPATFULL

Full Citing
 Text References

AN 93:74398 USPATFULL
 TI Polymers and copolymers of high glass transition temperature from
 hindered phenols
 IN Hay, Allan S., 5015 Glencairn Ave., Montreal, Quebec, Canada H3W 2B3
 Kim, Whan Gi, 3575 University Avenue, Montreal, Quebec, Canada H3A 2B1
 PI US 5243016 19930907
 AI US 1992-964900 19921022 (7)
 RLI Continuation of Ser. No. US 1991-683860, filed on 11 Apr 1991, now
 patented, Pat. No. US 5182358
 DT Utility
 FS Granted
 LN.CNT 624

INCL INCLM: 528/191.000
 INCLS: 252/404.000; 528/098.000; 528/125.000; 528/126.000; 528/128.000;
 528/219.000; 568/730.000
 NCL NCLM: 528/191.000
 NCLS: 252/404.000; 528/098.000; 528/125.000; 528/126.000; 528/128.000;
 528/219.000; 568/730.000
 IC [5]
 ICM: C07C039-12
 EXF 528/191; 528/98; 528/125; 528/126; 528/128; 528/219; 252/404; 524/341;
 524/351; 568/730
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 50 OF 55 USPATFULL

Full Text	Citing References
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AN 93:40101 USPATFULL
 TI **Polyarylene ethers**
 IN Pfaendner, Rudolf, Rimbach/Odenwald, Germany, Federal Republic of
 Kainmuller, Thomas, Lindenfels/Odenwald, Germany, Federal Republic of
 Hoffmann, Kurt, Lautertal, Germany, Federal Republic of
 Kramer, Andreas, Dudinglen, Switzerland
 Stockinger, Friedrich, Courtepin, Switzerland
 PA Ciba-Geigy Corporation, Ardsley, NY, United States (U.S. corporation)
 PI US 5212278 19930518
 AI US 1990-493058 19900313 (7)
 PRAI CH 1989-995 19890317
 DT Utility
 FS Granted
 LN.CNT 503
 INCL INCLM: 528/171.000
 INCLS: 528/125.000; 528/126.000; 528/128.000; 528/174.000; 528/175.000;
 528/219.000; 528/220.000; 528/226.000; 528/391.000; 525/390.000;
 525/534.000
 NCL NCLM: 528/171.000
 NCLS: 525/390.000; 525/534.000; 528/125.000; 528/126.000; 528/128.000;
 528/174.000; 528/175.000; 528/219.000; 528/220.000; 528/226.000;
 528/391.000
 IC [5]
 ICM: C08G075-23
 ICS: C08G008-02; C08G014-00; C08G065-38
 EXF 528/171; 528/128; 528/125; 528/174; 528/126; 528/175; 528/219; 528/220;
 528/391; 528/226; 525/390; 525/534
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 51 OF 55 USPATFULL

Full Text	Citing References
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AN 93:7190 USPATFULL
 TI Polymers and copolymers of high glass transition temperature from
 hindered phenols
 IN Hay, Allan S., 5015 Glencairn Ave., Montreal, Quebec, Canada H3W 2B3
 Kim, Whan Gi, 3575 University Avenue, Montreal, Quebec, Canada H3A 2B1
 PI US 5182358 19930126
 AI US 1991-683860 19910411 (7)
 DT Utility
 FS Granted
 LN.CNT 583
 INCL INCLM: 528/191.000
 INCLS: 252/404.000; 528/098.000; 528/125.000; 528/126.000; 528/128.000;
 528/219.000; 528/191.000; 568/730.000
 NCL NCLM: 528/191.000
 NCLS: 252/404.000; 528/098.000; 528/125.000; 528/126.000; 528/128.000;
 528/219.000; 568/730.000
 IC [5]

ICM: C07C039-12
 EXF 528/125; 528/126; 528/128; 528/219; 528/98; 528/171; 528/191; 525/437;
 525/450; 525/471; 525/397; 525/394; 524/425; 521/134
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 52 OF 55 USPATFULL

Full Citing
Text References

AN 91:10896 USPATFULL
 TI Temperature resistant aromatic polyethers
 IN Knebel, Joachim, Darmstadt, Germany, Federal Republic of
 Ude, Werner, Darmstadt, Germany, Federal Republic of
 Vetter, Joachim, Darmstadt, Germany, Federal Republic of
 PA Rohm GmbH, Darmstadt, Germany, Federal Republic of (non-U.S.
 corporation)
 PI US 4990588 19910205
 AI US 1989-308110 19890208 (7)
 PRAI DE 1988-3804988 19880218
 DT Utility
 FS Granted
 LN.CNT 499
 INCL INCLM: 528/125.000
 INCLS: 528/125.000; 528/167.000; 528/169.000; 528/398.000
 NCL NCLM: 528/125.000
 NCLS: 528/167.000; 528/169.000; 528/398.000
 IC [5]
 ICM: C08G008-02
 ICS: C08G079-02
 EXF 528/167; 528/169; 528/398; 528/125
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 53 OF 55 USPATFULL

Full Citing
Text References

AN 89:102293 USPATFULL
 TI Thermoplastic **polyarylene ethers**
 IN Besecke, Sigmund, Seeheim-Jugenheim, Germany, Federal Republic of
 Knebel, Joachim, Darmstadt, Germany, Federal Republic of
 Schroeder, Guenter, Ober-Ramstadt, Germany, Federal Republic of
 Ude, Werner, Darmstadt-Arheilgen, Germany, Federal Republic of
 PA Rohm GmbH, Darmstadt, Germany, Federal Republic of (non-U.S.
 corporation)
 PI US 4889909 19891226
 AI US 1988-221321 19880719 (7)
 PRAI DE 1987-3725058 19870729
 DT Utility
 FS Granted
 LN.CNT 374
 INCL INCLM: 528/125.000
 INCLS: 528/126.000; 528/219.000; 525/390.000; 525/394.000; 525/416.000;
 525/534.000
 NCL NCLM: 528/125.000
 NCLS: 525/390.000; 525/394.000; 525/416.000; 525/534.000; 528/126.000;
 528/219.000
 IC [4]
 ICM: C08G008-02
 EXF 528/125; 528/126; 528/219; 525/390; 525/394; 525/416; 525/534
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 54 OF 55 USPATFULL

Full Citing
Text References

AN 82:25462 USPATFULL
 TI Production of aromatic polyethers with infusible particulate substance

IN Staniland, Philip A., Tewin Wood, England
 PA Imperial Chemical Industries Limited, London, England (non-U.S.
 corporation)
PI US 4331798 19820525
AI US 1979-77476 19790920 (6)
RLI Continuation-in-part of Ser. No. US 1979-4532, filed on 18 Jan 1979, now
 abandoned
 DT Utility
 FS Granted
 LN.CNT 378
 INCL INCLM: 528/125.000
 INCLS: 528/126.000; 528/128.000; 528/174.000
 NCL NCLM: 528/125.000
 NCLS: 528/126.000; 528/128.000; 528/174.000
 IC [3]
 ICM: C08G008-02
 ICS: C08G075-20
 EXF 528/125; 528/126; 528/128; 528/174
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 55 OF 55 USPAT2

Full
 Citing
 Text
 References

AN 2001:169644 USPAT2
 TI Bonding process
 IN DeLouise, Lisa A., Rochester, NY, United States
 Luca, David J., Rochester, NY, United States
 PA Xerox Corporation, Stamford, CT, United States (U.S. corporation)
PI US 6485130 B2 20021126
AI US 2001-844371 20010427 (9)
RLI Division of Ser. No. US 1998-105501, filed on 26 Jun 1998, now patented,
 Pat. No. US 6273985
 DT Utility
 FS GRANTED
 LN.CNT 2657
 INCL INCLM: 347/063.000
 INCLS: 428/167.000; 347/064.000; 347/065.000
 NCL NCLM: 347/063.000
 NCLS: 347/064.000; 347/065.000; 428/167.000
 IC [7]
 ICM: B41J002-015
 EXF 347/20; 347/63; 347/64; 347/65; 428/167; 156/273.3

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